

V. Balasubramanian

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L1 STRUCTURE UPLOADED

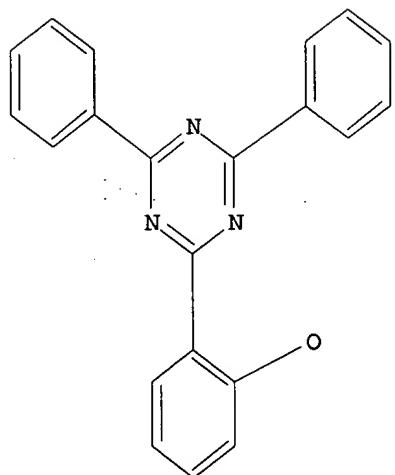
=> que L1

L2 QUE L1

=> d l1

L1 HAS NO ANSWERS
L1 STR

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=> s l1 sss sam

SAMPLE SEARCH INITIATED 13:21:57 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 78 TO ITERATE

100.0% PROCESSED 78 ITERATIONS 50 ANSWERS
INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)
SEARCH TIME: 00.00.01

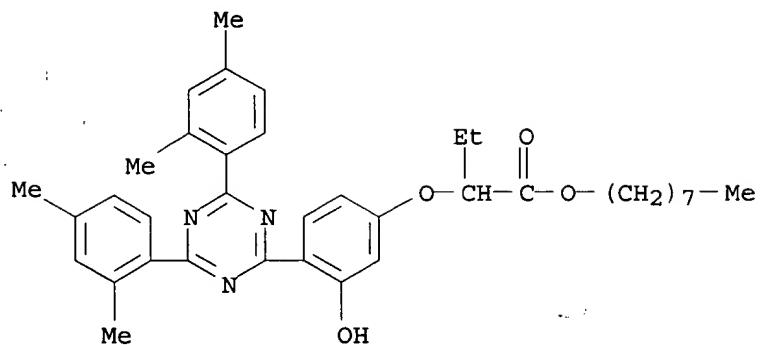
FULL FILE PROJECTIONS: ONLINE **COMPLETE**
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PROJECTED ITERATIONS: 1031 TO 2089
PROJECTED ANSWERS: 981 TO 2019

L3 50 SEA SSS SAM L1

=> d scan l3

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Butanoic acid, 2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-, octyl ester (9CI)
MF C37 H45 N3 O4

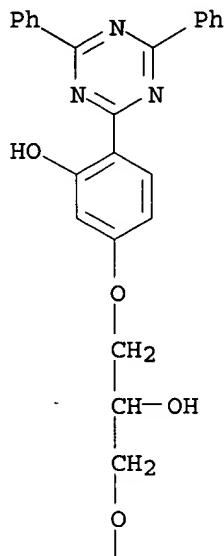
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HOW MANY MORE ANSWERS DO YOU WISH TO SCAN? (1) : 49

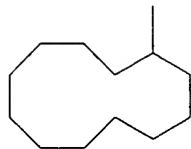
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 5-[3-(cyclododecyloxy)-2-hydroxypropoxy]-2-(4,6-diphenyl-1,3,5-triazin-2-yl)- (9CI)
MF C36 H43 N3 O4

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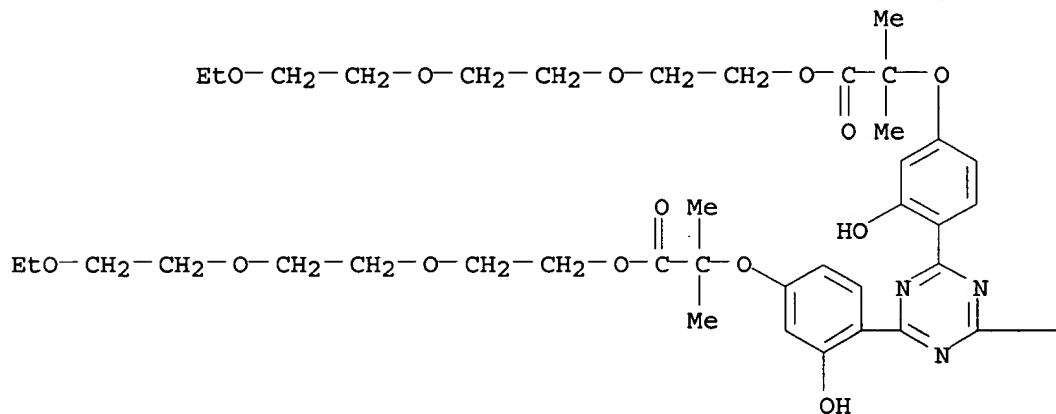


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

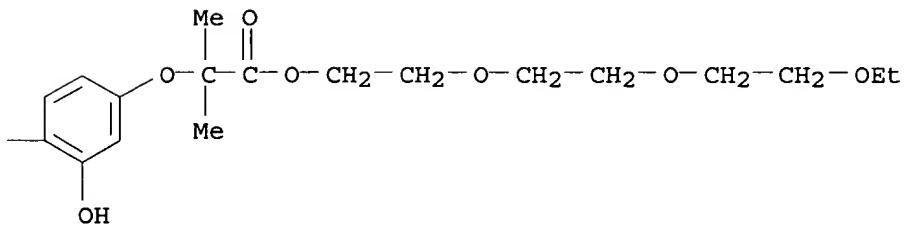
IN Propanoic acid, 2,2',2'''-[1,3,5-triazine-2,4,6-triyltris[(3-hydroxy-4,1-phenylene)oxy]]tris[2-methyl-, tris[2-[2-(2-ethoxyethoxy)ethoxy]ethyl]ester (9CI)

MF C57 H81 N3 021

PAGE 1-A

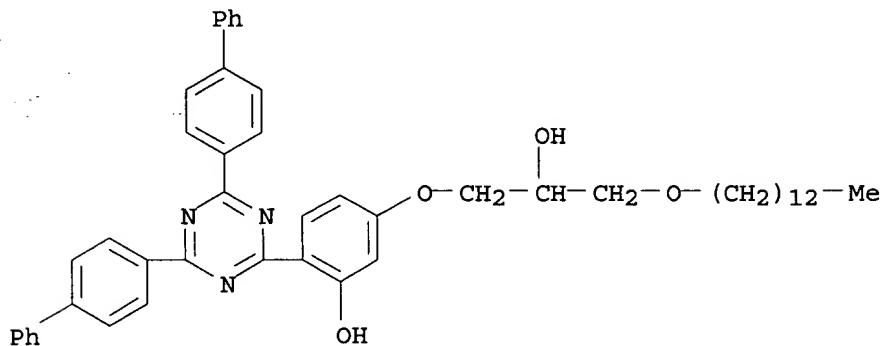


PAGE 1-B



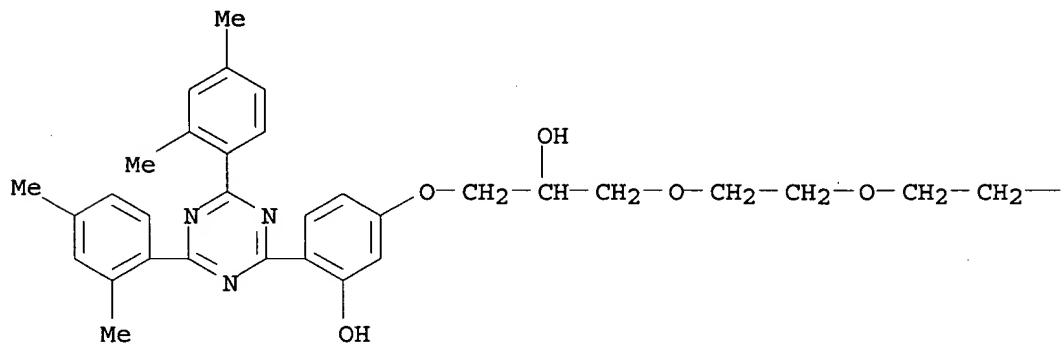
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L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol,
2-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-5-[2-hydroxy-
3-(tridecyloxy)propoxy] - (9CI)
MF C49 H55 N3 O4
CI COM



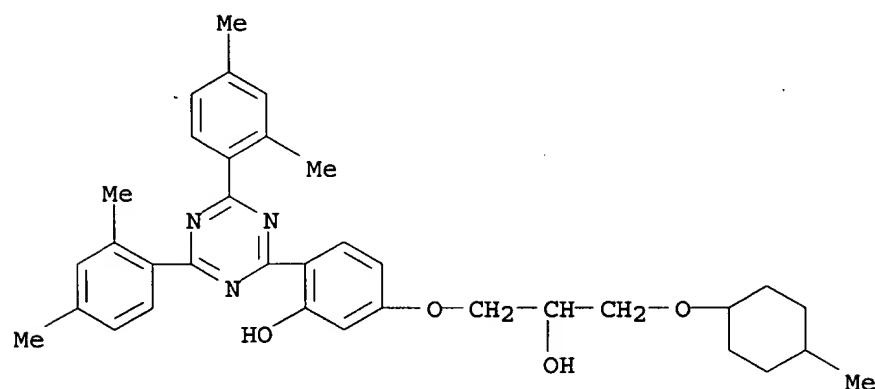
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 2,5,8,11-Tetraoxatetradecan-13-ol, 14-[4-[4,6-bis(2,4-dimethylphenyl)-
1,3,5-triazin-2-yl]-3-hydroxyphenoxy]- (9CI)
MF C35 H43 N3 O7

PAGE 1-A



— O— CH₂— CH₂— OMe

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol,
2-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-5-[2-hydroxy-3-
[(4-methylcyclohexyl)oxy]propoxy]- (9CI)
MF C35 H41 N3 O4

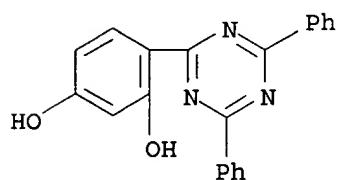


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Hiwax 1105A, ester with 4-(4,6-diphenyl-1,3,5-triazin-2-yl)-1,3-
benzenediol (9CI)
MF C21 H15 N3 O2 . x Unspecified

CM 1

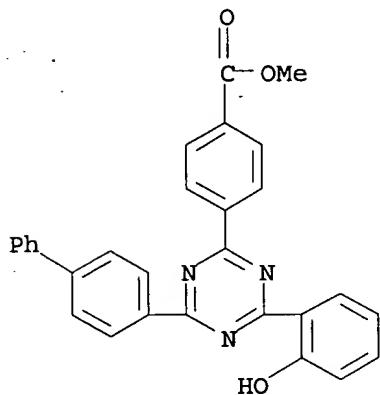
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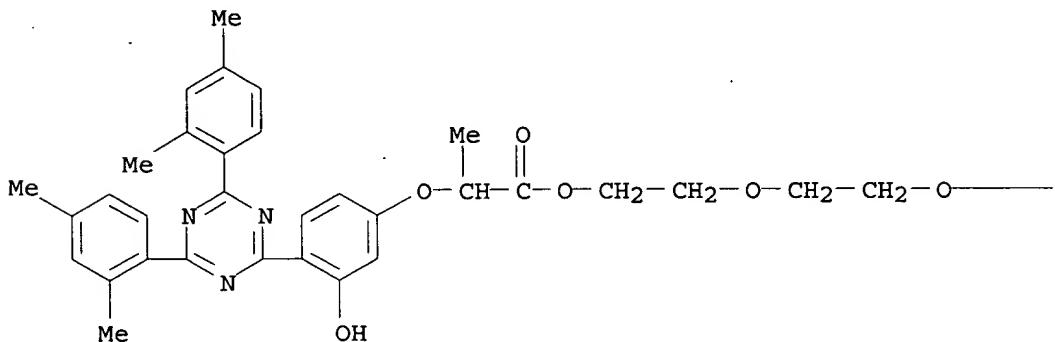
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L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Benzoic acid,
4-[4-[1,1'-biphenyl]-4-yl-6-(2-hydroxyphenyl)-1,3,5-triazin-2-yl]-, methyl ester (9CI)
MF C29 H21 N3 O3



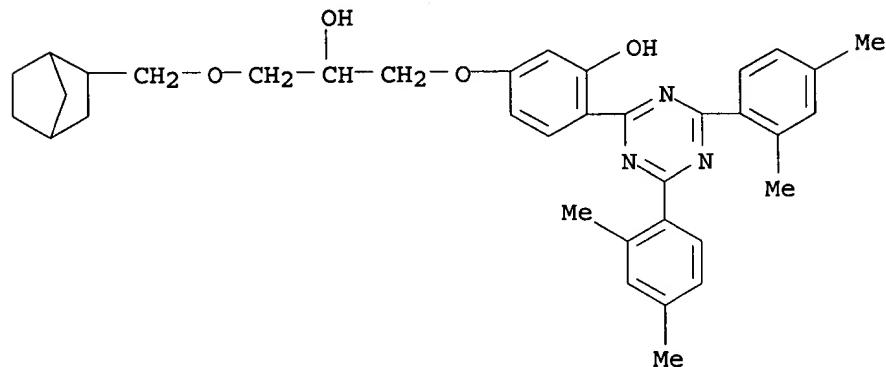
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Propanoic acid, 2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-, 2-[2-(2-butoxyethoxy)ethoxy]ethyl ester (9CI)
MF C38 H47 N3 O7

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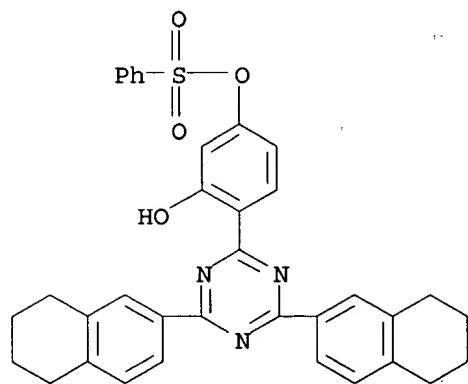
— CH₂— CH₂— OBu-n

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 5-[3-(bicyclo[2.2.1]hept-2-ylmethoxy)-2-hydroxypropoxy]-2-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]- (9CI)
MF C36 H41 N3 O4

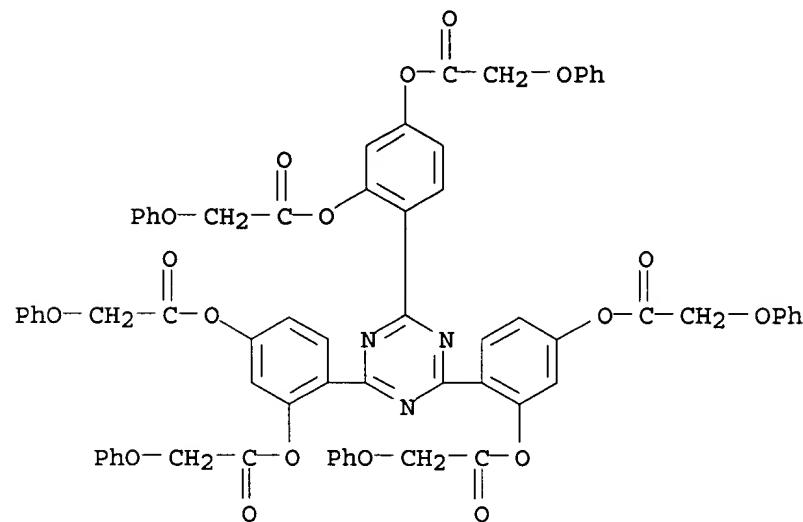


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 1,3-Benzenediol, 4-[4,6-bis(5,6,7,8-tetrahydro-2-naphthalenyl)-1,3,5-triazin-2-yl]-, 1-benzenesulfonate (9CI)
MF C35 H31 N3 O4 S

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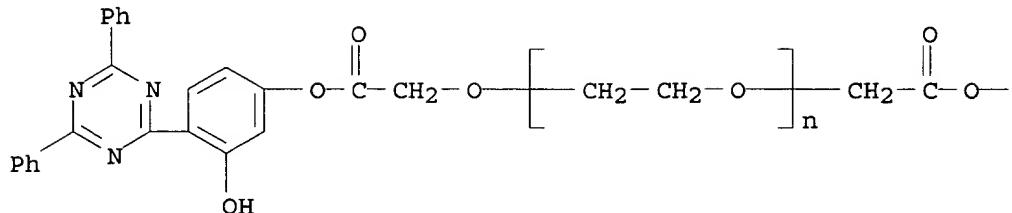
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Acetic acid, phenoxy-, 1,3,5-triazine-2,4,6-triyltri-1,2,4-benzenetriyl ester (9CI)
MF C69 H51 N3 O18



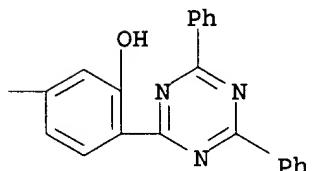
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Poly(oxy-1,2-ethanediyl),
.alpha.-[2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-
3-hydroxyphenoxy]-2-oxoethyl]..omega..-[2-[4-(4,6-diphenyl-1,3,5-triazin-2-
yl)-3-hydroxyphenoxy]-2-oxoethoxy]- (9CI)
MF (C2 H4 O)n C46 H32 N6 O7
CI PMS

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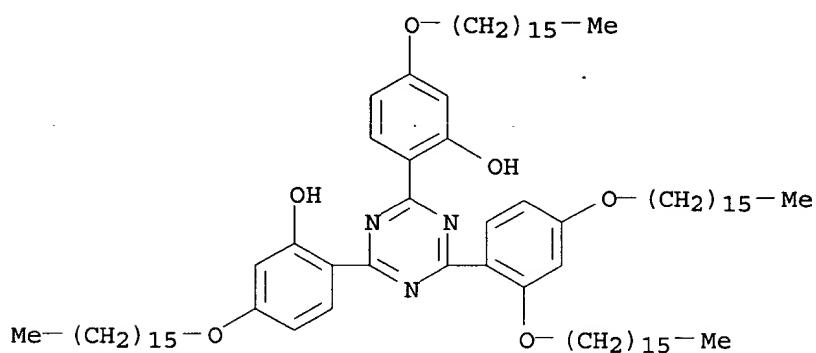
PAGE 1-A



PAGE 1-B



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2,2'-(6-[2,4-bis(hexadecyloxy)phenyl]-1,3,5-triazine-2,4-diyil)bis[5-(hexadecyloxy)- (9CI)
MF C85 H143 N3 O6

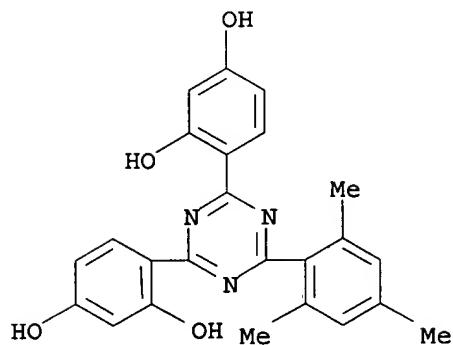


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN 1,3-Benzenedicarboxylic acid, polymer with 2,2-dimethyl-1,3-propanediol,
 2-ethyl-2-(hydroxymethyl)-1,3-propanediol, hexanedioic acid,
 3-hydroxy-2-(hydroxymethyl)-2-methylpropanoic acid,
 12-hydroxyoctadecanoic acid, methyl 2-methyl-2-propenoate, 2-methyl-2-propenoic acid,
 oxiranylmethyl 2-methyl-2-propenoate and 4,4'-(6-(2,4,6-trimethylphenyl)-
 1,3,5-triazine-2,4-diyl)bis[1,3-benzenediol] (9CI)

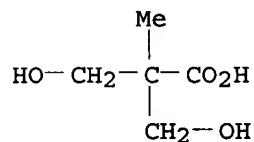
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MF (C₂₄ H₂₁ N₃ O₄ . C₁₈ H₃₆ O₃ . C₈ H₆ O₄ . C₇ H₁₀ O₃ . C₆ H₁₄ O₃ . C₆ H₁₀ O₄ . C₅ H₁₂ O₂ . C₅ H₁₀ O₄ . C₅ H₈ O₂ . C₄ H₆ O₂)_x
CI PMS

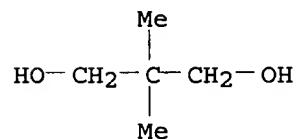
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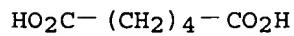
CM 2



CM 3

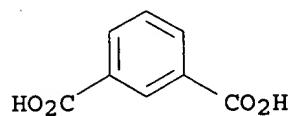


CM 4

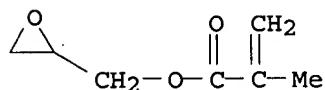


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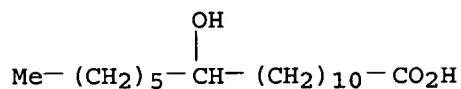
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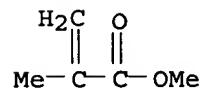
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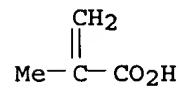
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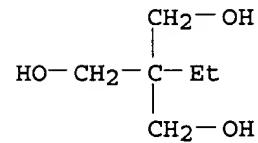
CM 8



CM 9

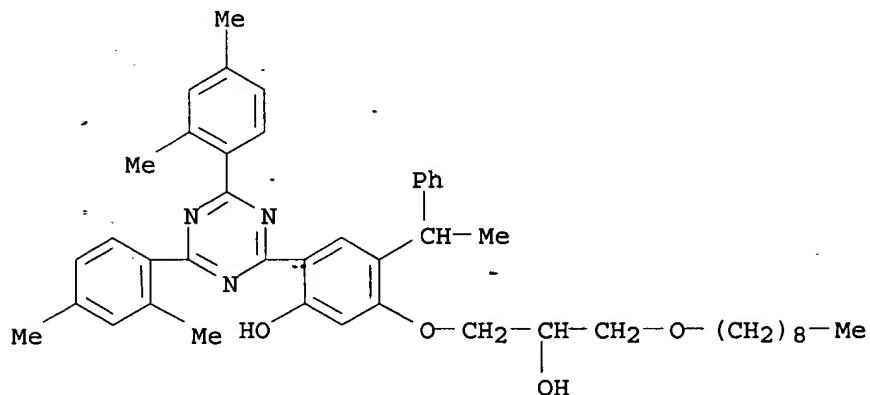


CM 10



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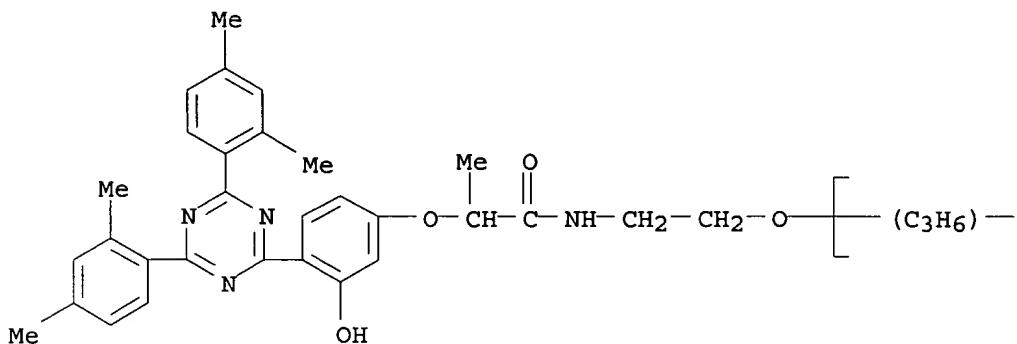
IN Phenol,
2-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-5-[2-hydroxy-3-(nonyloxy)propoxy]-4-(1-phenylethyl)- (9CI)
MF C45 H55 N3 O4



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

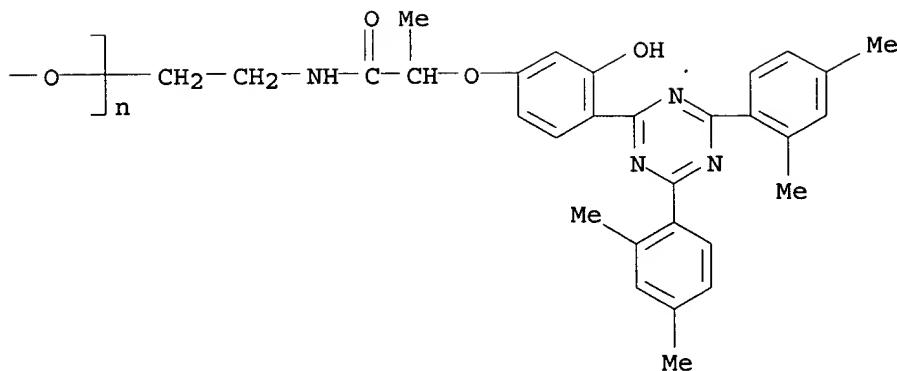
IN Poly[oxy(methyl-1,2-ethanediyl)], .alpha.-[2-[[2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-1-oxopropyl]amino]methylethyl]-.omega.-[2-[[2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-1-oxopropyl]amino]methylethoxy] - (9CI)
 MF (C₃ H₆ O)_n C₆₂ H₆₆ N₈ O₇
 CI IDS, PMS

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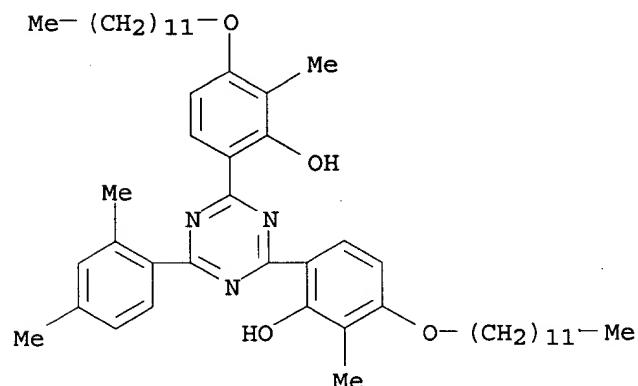
PAGE 1-B



PAGE 2-A

2 (D1-Me)

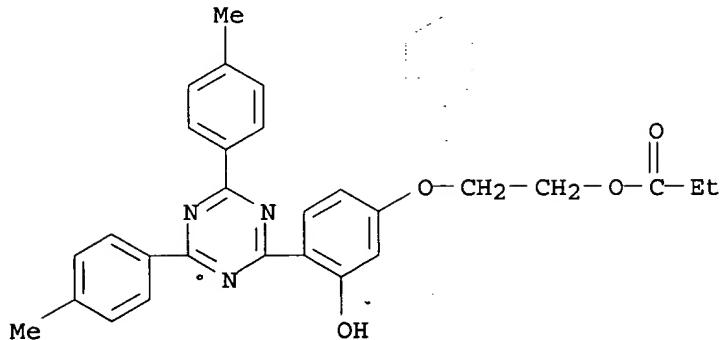
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2,2'-[6-(2,4-dimethylphenyl)-1,3,5-triazine-2,4-diyl]bis[5-(dodecyloxy)-6-methyl- (9CI)
MF C49 H71 N3 O4



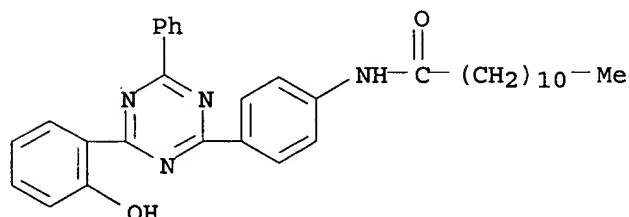
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2-[4,6-bis(4-methylphenyl)-1,3,5-triazin-2-yl]-5-[2-(1-

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oxopropoxy)ethoxy] - (9CI)
MF C28 H27 N3 O4



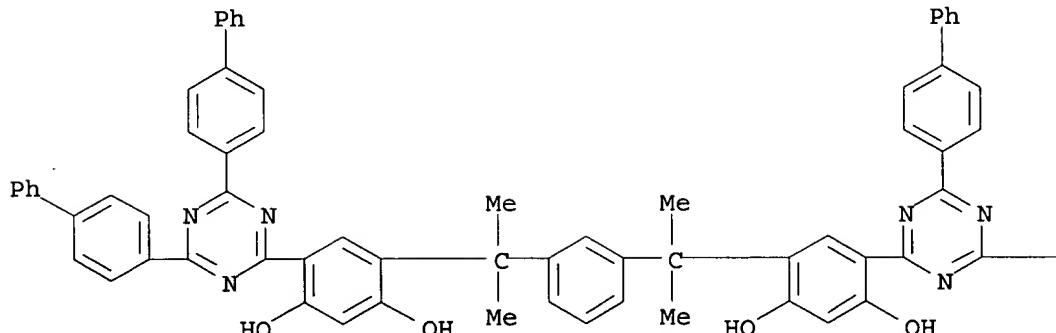
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Dodecanamide, N-[4-[(2-hydroxyphenyl)-6-phenyl-1,3,5-triazin-2-yl]phenyl] - (9CI)
MF C33 H38 N4 O2



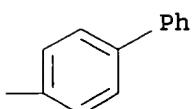
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 1,3-Benzenediol, 4,4'-(1,3-phenylenebis(1-methylethylidene))bis[6-[(4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl)amino]benzene] - (9CI)
MF C78 H60 N6 O4

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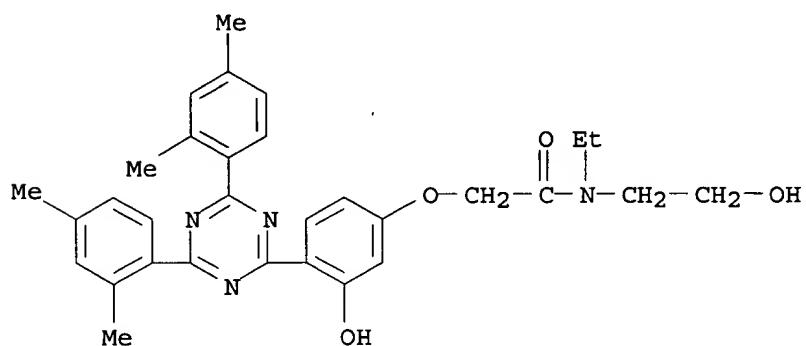
PAGE 1-A



PAGE 1-B



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Acetamide, 2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-N-ethyl-N-(2-hydroxyethyl)- (9CI)
MF C31 H34 N4 O4

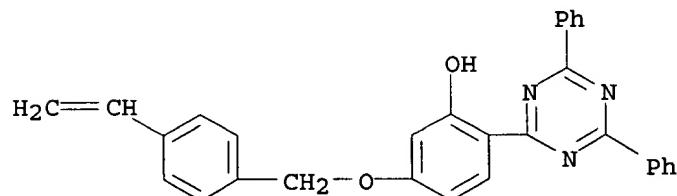


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 2-Propenoic acid, butyl ester, polymer with
2-(4,6-diphenyl-1,3,5-triazin-2-yl)-5-[(3-ethenylphenyl)methoxy]phenol and
2-(4,6-diphenyl-1,3,5-triazin-

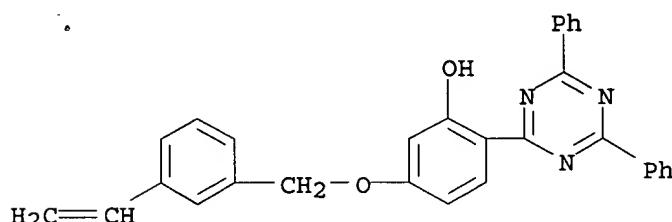
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2-yl)-5-[(4-ethenylphenyl)methoxy]phenol (9CI)
MF (C₃₀ H₂₃ N₃ O₂ . C₃₀ H₂₃ N₃ O₂ . C₇ H₁₂ O₂)_x
CI PMS

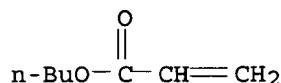
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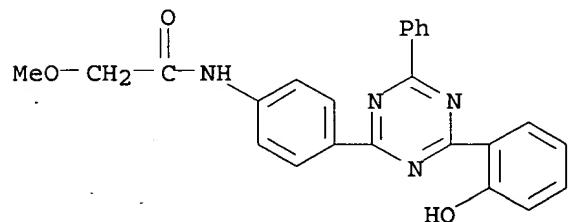
CM 2



CM 3



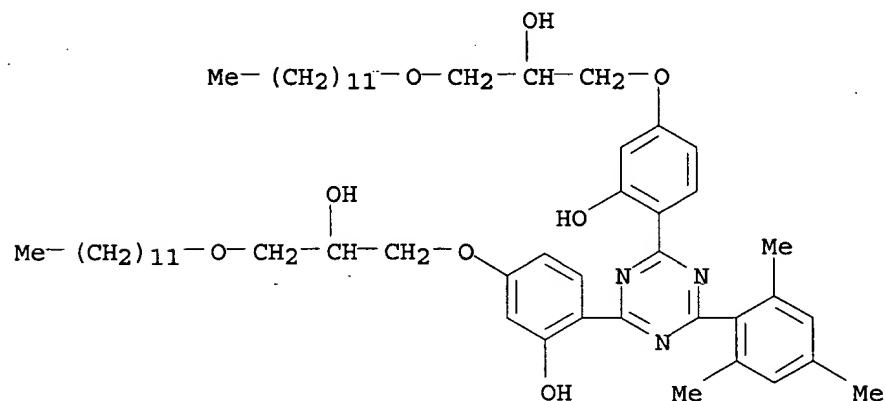
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Acetamide,
N-[4-[(4-((2-hydroxyphenyl)-6-phenyl-1,3,5-triazin-2-yl)phenyl]-2-methoxy- (9CI)
MF C₂₄ H₂₀ N₄ O₃



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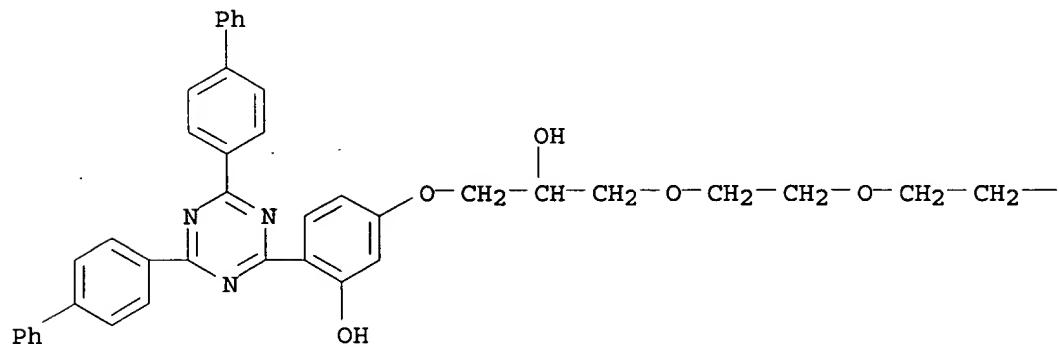
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 4,7,10,13-Tetraoxaheptadecan-2-ol, 1-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-, mixt. with 2,2'-[6-(2,4,6-trimethylphenyl)-1,3,5-triazine-2,4-diyl]bis[5-[3-(dodecyloxy)-2-hydroxypropoxy]phenol] (9CI)
MF C54 H81 N3 O8 . C46 H49 N3 O7
CI MXS

CM 1



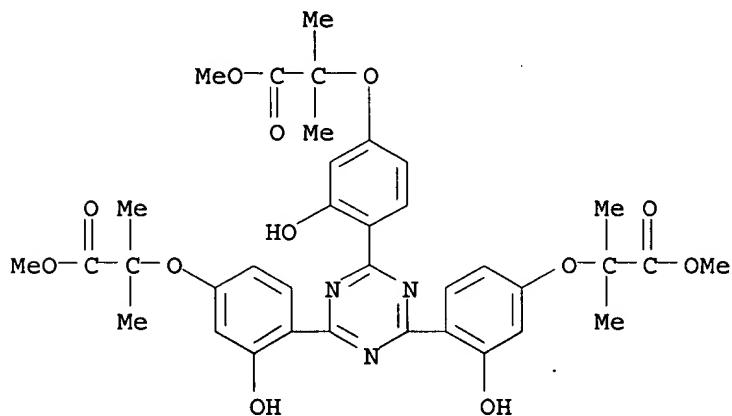
CM 2

PAGE 1-A



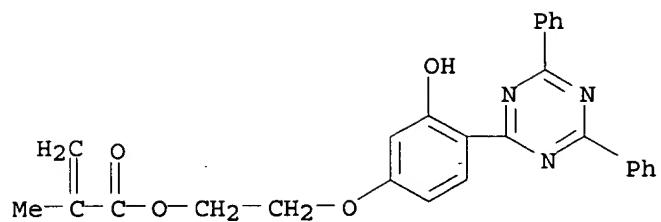
—O—CH₂—CH₂—OBu-n

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN Propanoic acid, 2,2',2'''-[1,3,5-triazine-2,4,6-triyltris[(3-hydroxy-4,1-phenylene)oxy]]tris[2-methyl-, trimethyl ester (9CI)
 MF C36 H39 N3 O12

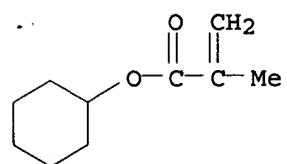


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with cyclohexyl 2-methyl-2-propenoate, 2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]ethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, methyl 2-propenoate and 2-propenoic acid (9CI)
 MF (C₂₇ H₂₃ N₃ O₄ . C₁₀ H₁₆ O₂ . C₈ H₁₄ O₂ . C₅ H₈ O₂ . C₄ H₆ O₂ . C₃ H₄ O₂)_x
 CI PMS

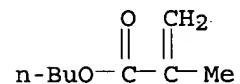
CM 1



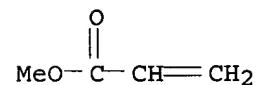
CM 2



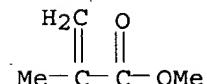
CM 3



CM 4

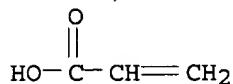


CM 5

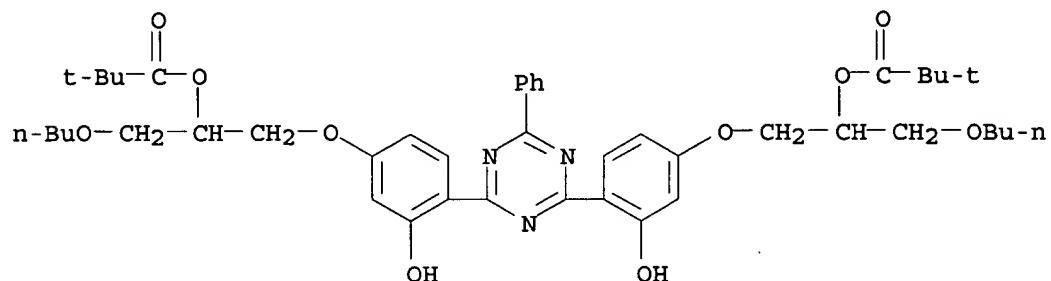


CM 6

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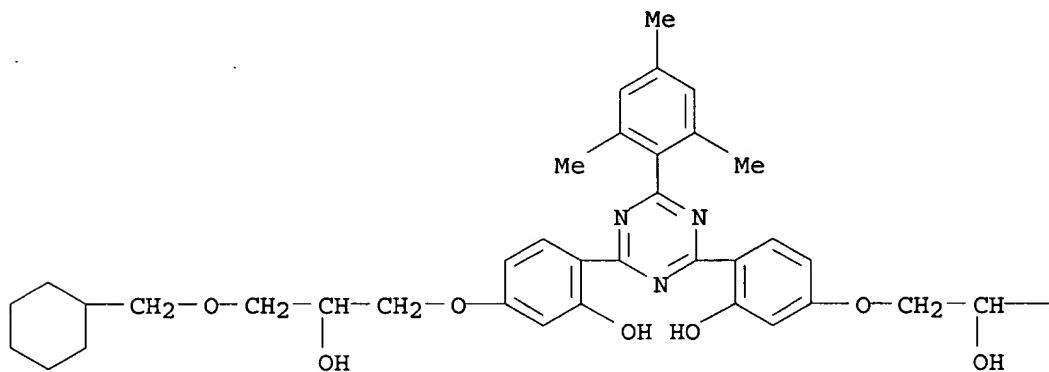


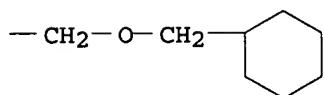
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Propanoic acid, 2,2-dimethyl-, (6-phenyl-1,3,5-triazine-2,4-diyl)bis[(3-hydroxy-4,1-phenylene)oxy[1-(butoxymethyl)-2,1-ethanediyl]] ester (9CI)
MF C45 H59 N3 O10



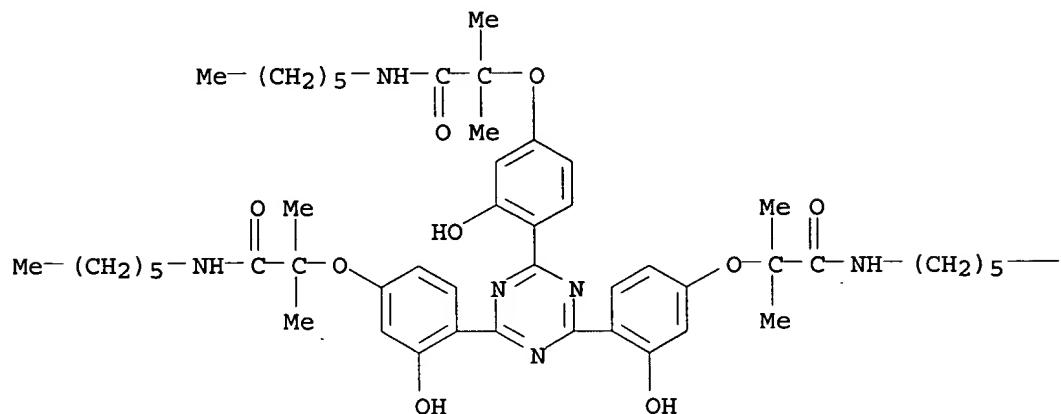
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2,2'-[6-(2,4,6-trimethylphenyl)-1,3,5-triazine-2,4-diyl]bis[5-[3-(cyclohexylmethoxy)-2-hydroxypropoxy]- (9CI)
MF C44 H57 N3 O8

PAGE 1-A





L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Propanamide, 2,2',2''-[1,3,5-triazine-2,4,6-triyltris[(3-hydroxy-4,1-phenylene)oxy]]tris[N-hexyl-2-methyl- (9CI)
MF C51 H72 N6 O9

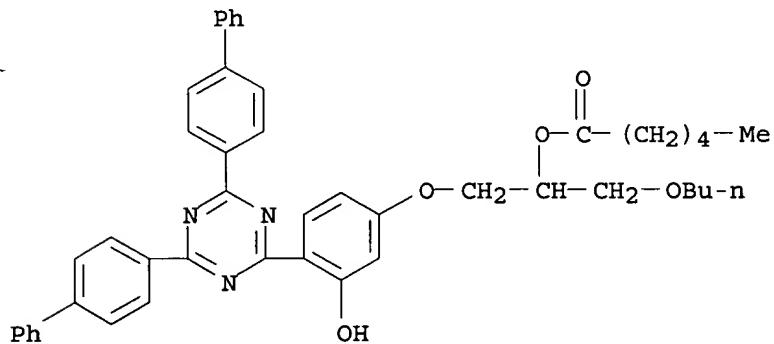


V. Balasubramanian

PAGE 1-B

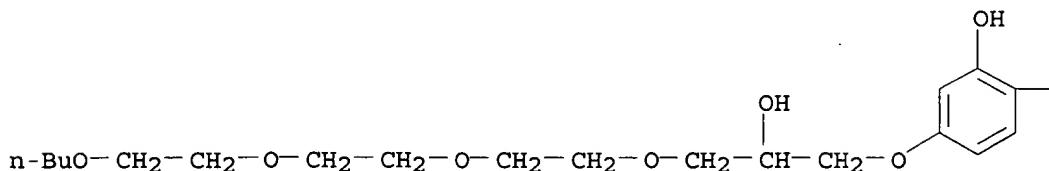
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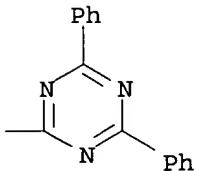
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Hexanoic acid, 2-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-1-(butoxymethyl)ethyl ester (9CI)
MF C46 H47 N3 O5



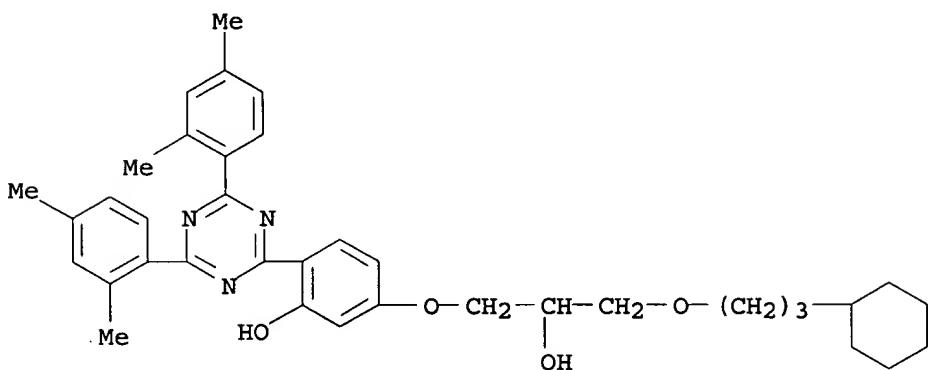
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 4,7,10,13-Tetraoxaheptadecan-2-ol,
1-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]- (9CI)
MF C34 H41 N3 O7

PAGE 1-A

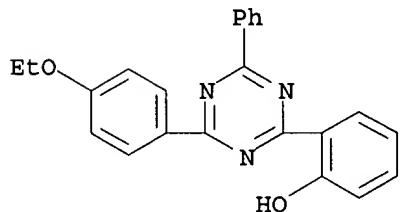




L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-5-[3-(3-cyclohexylpropoxy)-2-hydroxypropoxy] - (9CI)
MF C37 H45 N3 O4

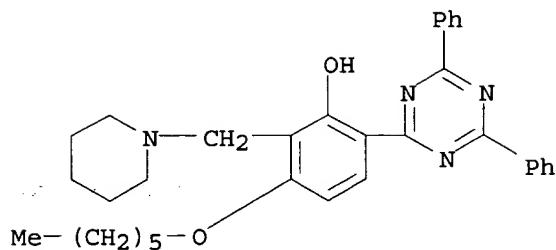


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2-[4-(4-ethoxyphenyl)-6-phenyl-1,3,5-triazin-2-yl]- (9CI)
MF C23 H19 N3 O2



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 6-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-(hexyloxy)-2-(1-piperidinylmethyl) - (9CI)
MF C33 H38 N4 O2

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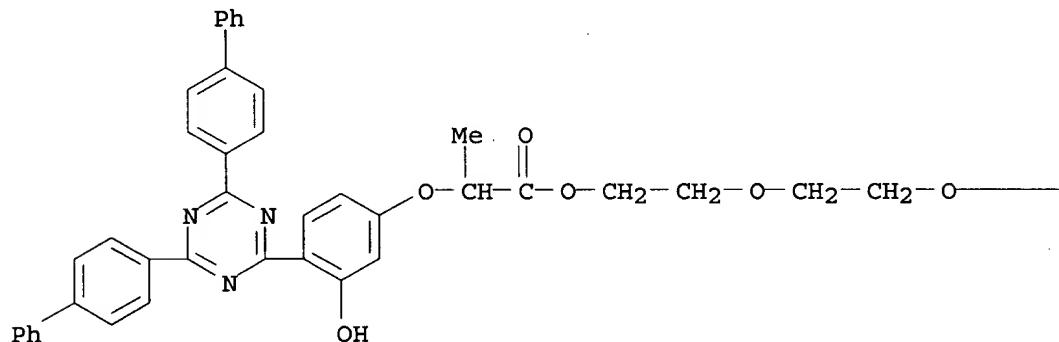
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

IN Propanoic acid,

2-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-2-[2-(2-methoxyethoxy)ethoxy]ethyl ester (9CI)

MF C43 H41 N3 O7

PAGE 1-A



PAGE 1-B

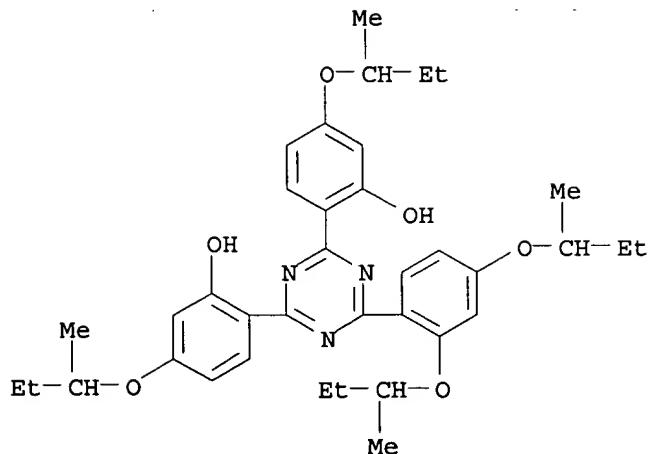
—CH₂—CH₂—OMe

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

IN Phenol, 2,2'-(6-[2,4-bis(1-methylpropoxy)phenyl]-1,3,5-triazine-2,4-diyl)bis[5-(1-methylpropoxy)phenol] (9CI)

MF C37 H47 N3 O6

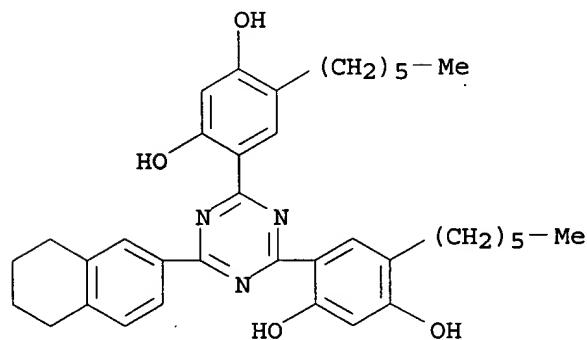
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L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

IN 1,3-Benzenediol, 4,4'-(6-(5,6,7,8-tetrahydro-2-naphthalenyl)-1,3,5-triazine-2,4-diyl)bis[6-hexyl- (9CI) ..

MF C37 H45 N3 O4



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

IN Silanediol, hexylmethyl-, polymer with

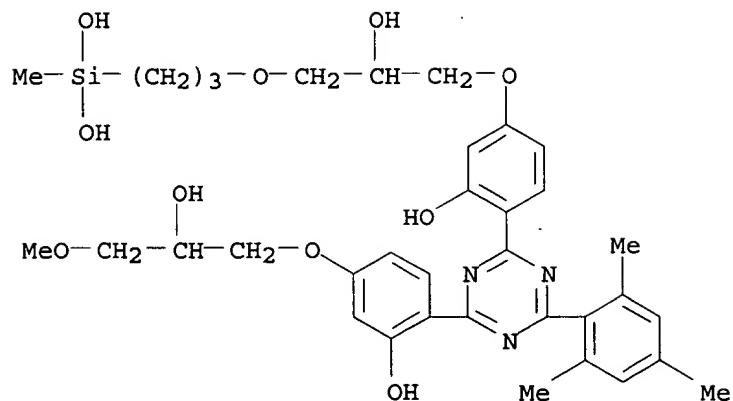
[3-[2-hydroxy-3-[3-hydroxy-4-[4-[2-hydroxy-4-(2-hydroxy-3-methoxypropoxy)phenyl]-6-(2,4,6-trimethylphenyl)-1,3,5-triazin-2-yl]phenoxy]propoxy]propyl]methylsilanediol (9CI)

MF (C35 H45 N3 O10 Si . C7 H18 O2 Si)x

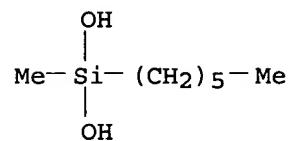
CI PMS

CM 1

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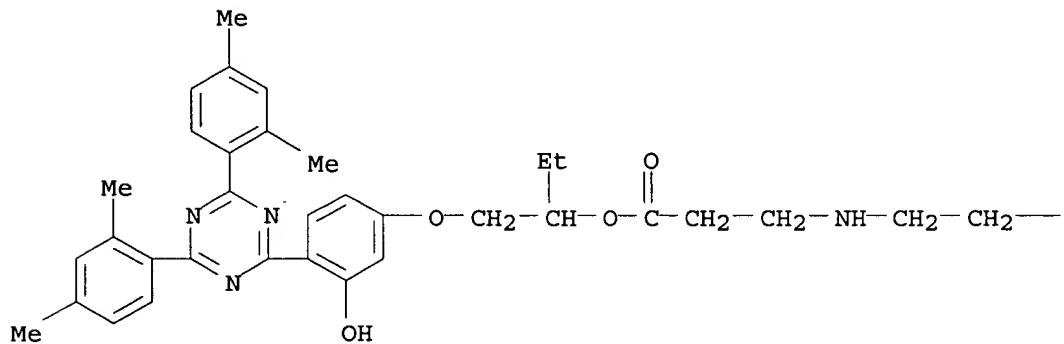


CM 2



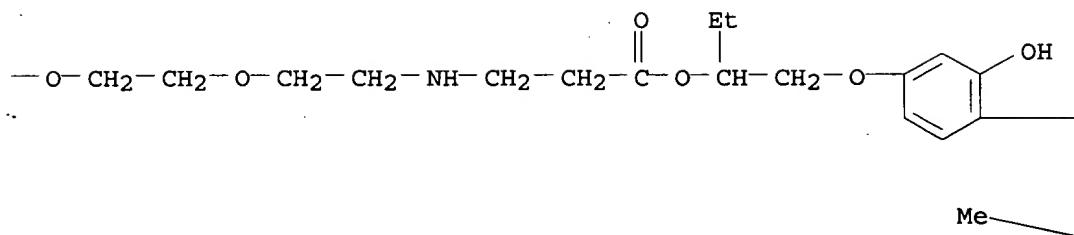
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 7,10-Dioxa-4,13-diazahexadecanoic acid, bis[1-[[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]methyl]propyl] ester (9CI)
MF C70 H82 N8 O10

PAGE 1-A



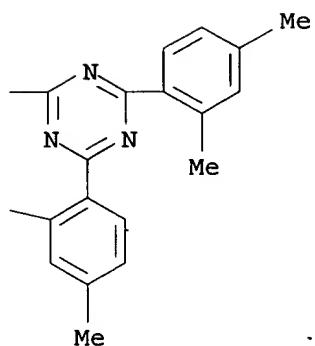
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PAGE 1-B



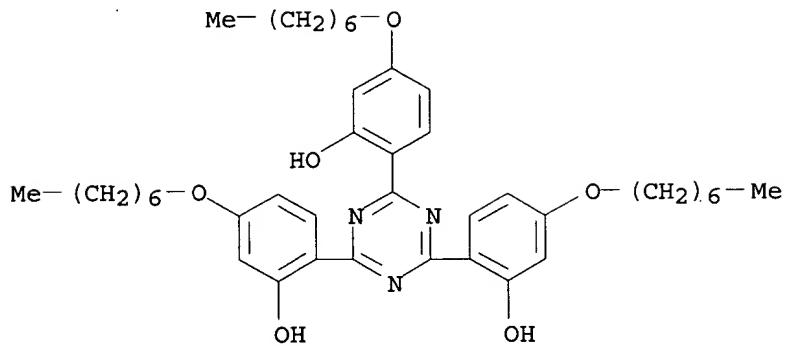
Me

PAGE 1-C

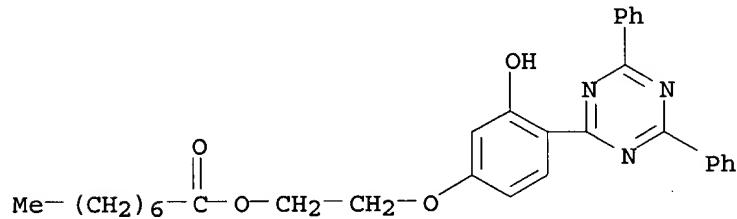


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2,2',2'''-(1,3,5-triazine-2,4,6-triyl)tris[5-(heptyloxy)- (9CI)
MF C42 H57 N3 O6

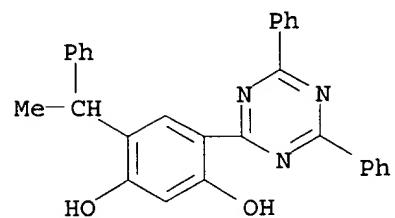
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L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Octanoic acid, 2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]ethyl ester (9CI)
MF C31 H33 N3 O4

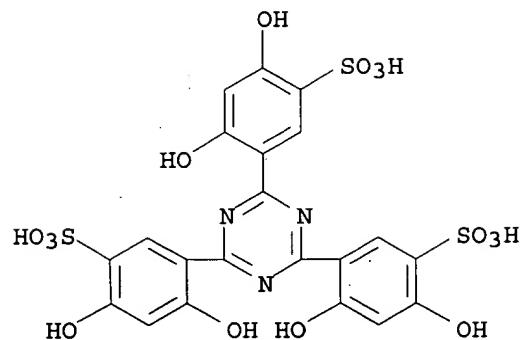


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 1,3-Benzenediol, 4-(4,6-diphenyl-1,3,5-triazin-2-yl)-6-(1-phenylethyl) - (9CI)
MF C29 H23 N3 O2

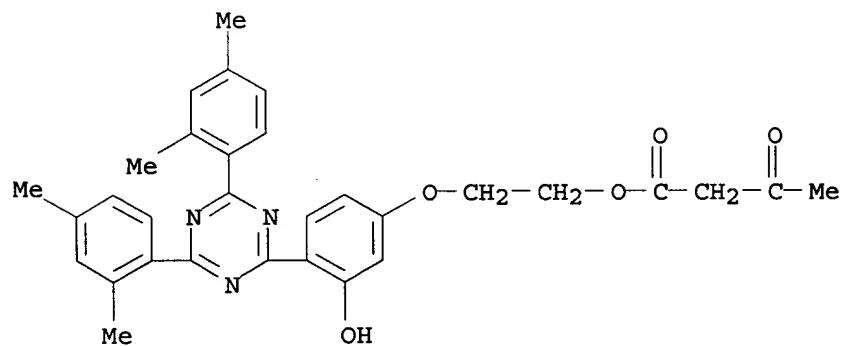


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Benzenesulfonic acid, 3,3',3'''-(1,3,5-triazine-2,4,6-triyl)tris[4,6-dihydroxy- (9CI)
MF C21 H15 N3 O15 S3

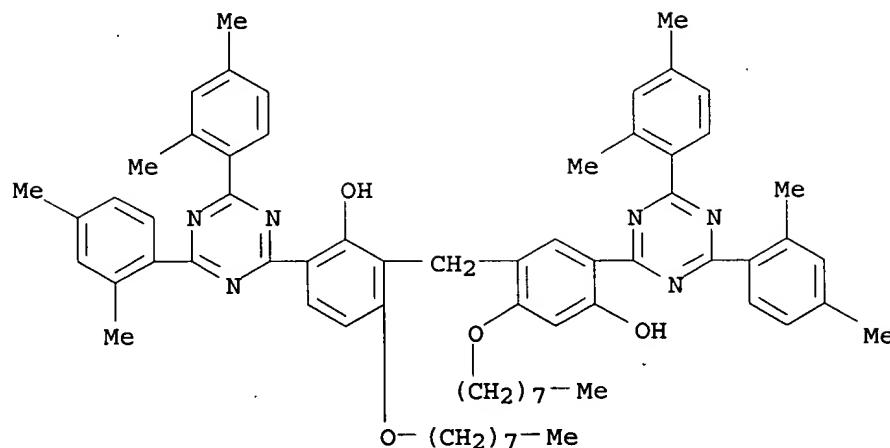
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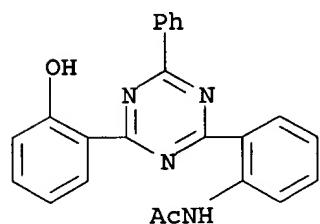
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Butanoic acid, 3-oxo-, 2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]ethyl ester (9CI)
MF C31 H31 N3 O5



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 6-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-2-[[5-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-4-hydroxy-2-(octyloxy)phenyl]methyl]-3-(octyloxy)- (9CI)
MF C67 H78 N6 O4

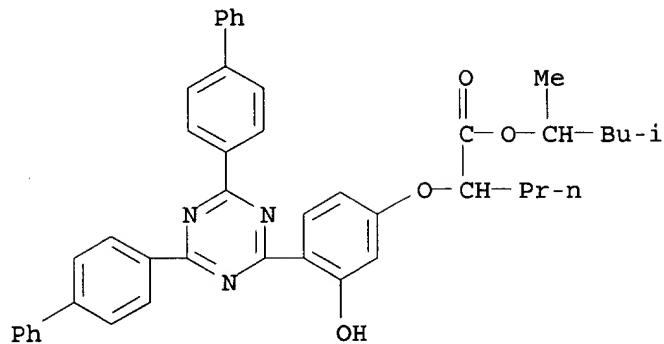


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Acetamide, N-[2-[4-(2-hydroxyphenyl)-6-phenyl-1,3,5-triazin-2-yl]phenyl]-
(9CI)
MF C23 H18 N4 O2



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Pentanoic acid,
2-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-
hydroxyphenoxy]-, 1,3-dimethylbutyl ester (9CI)
MF C44 H43 N3 O4

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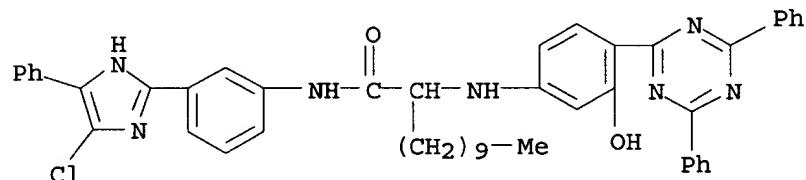


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

IN Dodecanamide,

N-[3-(4-chloro-5-phenyl-1H-imidazol-2-yl)phenyl]-2-[(4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenyl)amino]- (9CI)

MF C48 H48 Cl N7 O2



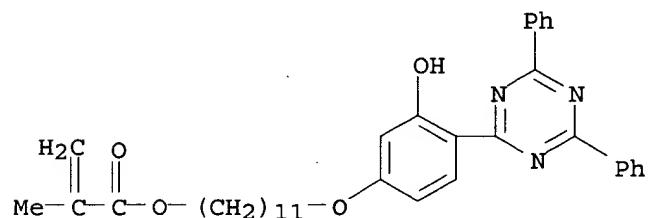
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

IN 2-Propenoic acid, 2-methyl-, 11-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]undecyl ester, polymer with methyl 2-methyl-2-propenoate (9CI)

MF (C36 H41 N3 O4 . C5 H8 O2)x

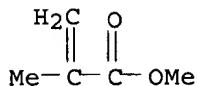
CI PMS

CM 1



CM 2

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ALL ANSWERS HAVE BEEN SCANNED

=> log y

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.93	1.08

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LOGINID:ssspta1611bxv
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NEWS 4 Feb 16 TOXLINE no longer being updated
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NEWS 7 May 07 DGENE Reload
NEWS 8 Jun 20 Published patent applications (A1) are now in USPATFULL
NEWS 9 JUL 13 New SDI alert frequency now available in Derwent's
DWPI and DPCI
NEWS 10 Aug 23 In-process records and more frequent updates now in
MEDLINE
NEWS 11 Aug 23 PAGE IMAGES FOR 1947-1966 RECORDS IN CAPLUS AND CA
NEWS 12 Aug 23 Adis Newsletters (ADISNEWS) now available on STN
NEWS 13 Sep 17 IMSworld Pharmaceutical Company Directory name change
to PHARMASEARCH

NEWS EXPRESS August 15 CURRENT WINDOWS VERSION IS V6.0C,
CURRENT MACINTOSH VERSION IS V6.0 (ENG) AND V6.0J (JP),
AND CURRENT DISCOVER FILE IS DATED 07 AUGUST 2001
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FILE LAST UPDATED: 30 Sep 2001 (20010930/ED)

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=> s triazine/cns

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L2 93410 L1

=> s 12 and (lewis(l)acid)
36804 LEWIS
3010872 ACID
17534 LEWIS(L)ACID
L3 105 L2 AND (LEWIS(L)ACID)

=> s 3 and Friedel(l)craft
5044811 3
13520 FRIEDEL
1400 CRAFT
546 FRIEDEL(L)CRAFT
L4 296 3 AND FRIEDEL(L)CRAFT

=> 3 and friedel
3 IS NOT A RECOGNIZED COMMAND
The previous command name entered was not recognized by the system.
For a list of commands available to you in the current file, enter
"HELP COMMANDS" at an arrow prompt (=>).

=> s 3 and friedel
5044811 3
13520 FRIEDEL
L5 6974 3 AND FRIEDEL

=> s 13 and Friedel(l)craft
13520 FRIEDEL
1400 CRAFT
546 FRIEDEL(L)CRAFT
L6 0 L3 AND FRIEDEL(L)CRAFT

=> s 13 and (cpmplex or promoter or initiator)
0 CPMPLEX
113986 PROMOTER
46088 INITIATOR
L7 3 L3 AND (CPMPLEX OR PROMOTER OR INITIATOR)

=> s 13 and (complex or promoter or initiator)
951602 COMPLEX
113986 PROMOTER
46088 INITIATOR
L8 12 L3 AND (COMPLEX OR PROMOTER OR INITIATOR)

=> d bib abs 1-12

L8 ANSWER 1 OF 12 CAPLUS COPYRIGHT 2001 ACS

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AN 2000:351512 CAPLUS

DN 132:347592

TI Preparation of 2-halo-4,6-diaryltriazines from cyanuric halides and arenes

using a combination of Lewis acids and reaction promoters.

IN Gupta, Ram B.; Jakiela, Dennis J.; Venimadhavan, Sampath; Cappadona, Russell C.; Pai, Venkatrao K.

PA Cytec Technology Corp., USA

SO PCT Int. Appl., 80 pp.

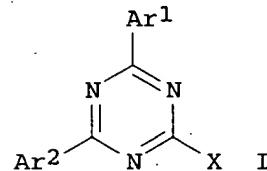
CODEN: PIXXD2

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2000029392	A1	20000525	WO 1999-US27253	19991117
	W: AE, AL, AM, AU, AZ, BA, BB, BG, BR, BY, CA, CN, CU, CZ, EE, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LV, MA, MD, MG, MK, MN, MW, MX, NO, NZ, PL, RO, RU, SD, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
	RW: GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG				
	EP 1131305	A1	20010912	EP 1999-960428	19991117
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	US 2001020094	A1	20010906	US 2001-779597	20010209
PRAI	US 1998-108786	P	19981117		
	US 1999-442000	A3	19991117		
	WO 1999-US27253	W	19991117		
OS	CASREACT 132:347592; MARPAT 132:347592				
GI					



AB Title compds. [I; Ar1, Ar2 = (substituted) Ph; X = halo], were prep'd. by reaction of arenes with cyanuric halides in the presence of a reaction facilitator comprising .gtoreq.1 Lewis acid and .gtoreq.1 reaction promoter, optionally in the presence of .gtoreq.1 solvent. Thus, cyanuric chloride and AlCl3 in PhCl at ice temp.

were treated with conc. HCl and m-xylene to give 95% 2-chloro-4,6-bis(2,4-dimethylphenyl)-1,3,5-triazine.

RE.CNT 9

RE

(1) Asahi Kasei Kogyo Kk; JP 06298674 A 1994 CAPLUS

V. Balasubramanian

(2) Brunetti, H; HELVETICA CHIMICA ACTA 1972, V55(5), P1566 CAPLUS
(3) Ciba Geigy; US 5726310 A CAPLUS
(4) Ciba Geigy; EP 0779280 A 1997 CAPLUS
(5) Ciba Geigy Ag; EP 0165608 A 1985 CAPLUS
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L8 ANSWER 2 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 2000:266352 CAPLUS
DN 132:295215
TI Rapidly active energy ray-curable coating compositions and their film formation
IN Maruyama, Tsutomu; Seko, Kenji; Miyakawa, Kenji; Ichimura, Kunihiro
PA Kansai Paint Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000119557	A2	20000425	JP 1998-292094	19981014
AB	The compns. contain 100 parts melamine resin or its mixts. with acrylic resins, polyesters, and/or alkyd resins, 0.01-10 parts photocationic polymn. initiators which generate Bronsted acids or Lewis acids upon active energy ray irradn., and 0.05-10 parts acid amplifiers catalyzed by the acids generated by the photocationic initiators. Thus, a compn. contg. butylated melamine resin 167, CyraCure UVI 6990 (initiator) 1, and cis-3-(p-toluenesulfonyloxy)-2-pinanol 1 part was applied on an epoxy-primed Al sheet, UV-irradiated, and heated at 110.degree. for 15 min to form a film showing pencil hardness H and good solvent resistance.				

L8 ANSWER 3 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1999:388571 CAPLUS
DN 131:80820
TI Production method of transparent hologram
IN Ito, Hiromitsu; Ohe, Yasushi
PA Toppan Printing Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11161137	A2	19990618	JP 1997-325028	19971126
AB	The method involves forming a film comprising a hologram recording material, on a substrate, contg. (A) a cationic polymerizable solvent-sol. thermosetting epoxy oligomer having .gtoreq.1 glycidyl group, (B) a radical polymerizable ethylenic unsatd. bond-contg. aliph. monomer which is liq. at room temp. and atm. and has boiling temp. .gtoreq.100.degree. at atm., (C) a photoinitiator which generates a Broensted acid or Lewis acid by chem. radiation exposure, and (D) a dye sensitizing agent, (2) holog. exposing, (3) developing, and (4)				

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irradiating with a visible light with wavelength 200-800 nm at 40-150.degree.. The hologram shows high sensitivity to visible light, excellent weather and heat resistance, durability, and good holog. properties such as resoln., transparency, etc.

L8 ANSWER 4 OF 12 CAPLUS COPYRIGHT 2001 ACS
 AN 1999:181614 CAPLUS
 DN 130:237997
 TI Highly branched olefin polymers and their uses
 IN Brookhart, Maurice S.; Johnson, Lynda Kaye; Killian, Christopher Moore; McCord, Elizabeth Forrester; McLain, Stephan James; Kreutzer, Kristina Ann; Ittel, Steven Dale; Tempel, Daniel Joseph
 PA E. I. Du Pont De Nemours and Company, USA
 SO U.S., 122 pp., Cont.-in-part of U.S. Ser. No. 473,590, abandoned.
 CODEN: USXXAM
 DT Patent
 LA English
 FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5880241	A	19990309	US 1996-590650	19960124
	US 5866663	A	19990202	US 1997-891332	19970710
	US 5880323	A	19990309	US 1997-891331	19970710
	US 5886224	A	19990323	US 1997-891403	19970710
	US 5891963	A	19990406	US 1997-891442	19970710
	US 5916989	A	19990629	US 1997-891472	19970710
	US 6034259	A	20000307	US 1997-891398	19970710
	US 6107422	A	20000822	US 1997-899003	19970710
	US 6140439	A	20001031	US 1997-891405	19970710
	US 6218493	B1	20010417	US 1997-891224	19970710
PRAI	US 1995-378044	B2	19950124		
	US 1995-415283	B2	19950403		
	US 1995-473590	B2	19950607		
	US 1995-2654	P	19950822		
	US 1995-7375	P	19951115		
	US 1996-590650	A3	19960124		

AB Disclosed herein are processes for polymg. ethylene, acyclic olefins, and/or selected cyclic olefins, and optionally selected olefinic esters or

carboxylic acids, and other monomers. The polymns. are catalyzed by selected transition metal compds., and sometimes other cocatalysts.

Since

some of the polymns. exhibit some characteristics of living polymns., block copolymers can be readily made. The polyolefins contain 80-150 branches/1000 CH₂ groups and 30-90 Et, 4-20 Pr, 15-50 Bu, 3-15 amyl, and 30-140 hexyl or longer branches per 100 Me branches. Numerous novel catalysts are disclosed, as well as some novel processes for making them. The polymers made are useful as elastomers, molding resins, in adhesives, etc. Also described herein is the synthesis of linear .alpha.-olefins by the oligomerization of ethylene using as a catalyst system a combination

a

nickel compd. having a selected .alpha.-diimine ligand and a selected Lewis or Bronsted acid, or by contacting selected .alpha.-diimine nickel complexes with ethylene. A typical catalyst was manufd. by stirring 10 mL MeOH contg. 1 mL HCO₂H, 5 mmol 2-tert-butylaniline, and 15.4 mmol 2,3-butanedione overnight, and stirring

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10 mL MeCN contg. 0.395 mmol resulting intermediate 5 min with (1,5-cyclooctadienyl) (methyl)acetonitrilepalladium hexafluoroantimonate.

RE.CNT 42

RE

(1) Anderson; US 3265622 1966 CAPLUS
(2) Anon; GB 1034197 1966 CAPLUS
(4) Anon; FR 2355854 1977 CAPLUS
(5) Anon; GB 2058094 1980 CAPLUS
(6) Anon; EP 0193202 A2 1986 CAPLUS

ALL CITATIONS AVAILABLE IN THE RE FORMAT

L8 ANSWER 5 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1997:765323 CAPLUS
DN 128:108480
TI Photopolymerizable compositions with high-laser sensitivity and lithographic plates using the same
IN Matsumoto, Shinji; Kuroki, Takaaki; Hattori, Yoshiji; Maehashi, Tatsuichi
PA Konica Co., Japan
SO Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09309907	A2	19971202	JP 1996-125657	19960521

AB Title compns., showing high sensitivity with laser exposure, include (A) ethylenically-unsatd. monomers, (B) Lewis acids MX_n (M = B, Al, Fe, Sn, Zn; X = halo; n = 1-3), and (C) onium salts, halo-contg. triazine compds., Fe-arene complexes, and/or bisimidazoles. The A and B may be microcapsuled. Title lithog. plates have layers of above compns. on hydrophilic supports.

L8 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1996:554708 CAPLUS
DN 125:171363
TI Decorative boards for pachinko pinball machines
IN Shioda, Yozo; Nakagawa, Hiroshi
PA Sumitomo Bakelite Co, Japan
SO Jpn. Kokai Tokkyo Koho, 4 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08156214	A2	19960618	JP 1994-295386	19941129

AB Decorative paper is impregnated with aq. melamine resin varnishes contg. water-sol. blocked isocyanates and Lewis acid-Mg complexes to prep. decorative boards. Thus, decorative paper was impregnated with a varnish contg. a melamine resin 100, powd. cellulose 2, silica 4, a Me Et ketoxime-blocked isocyanate 1.5, and a Lewis acid-Mg complex 0.2 part to prep. a decorative sheet and pressed on a phenolic resin core to prep. a pachinko board.

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L8 ANSWER 7 OF 12 CAPLUS COPYRIGHT 2001 ACS

AN 1995:677388 CAPLUS

DN 123:55587

TI Method of preparing 2,7-[2-(2-aminothiazol-4-yl)-2-

(methoxyiminoacetylarnino)]-3'--(2-methyl-5,6-dioxo-1,2,5,6-tetrahydro-1,2,4-triazin-3-ylthio)deacetoxycephalosporanic acid [ceftriaxone]

IN Winiarski, Jerzy; Grochowski, Edward; Prosciewicz, Boguslaw; Pankowski, Jacek; Boleslawska, Teresa; Cieslak, Marek; Gwiazda, Piotr; Szymanski, Jerzy; Nowakowska, Krystyna; Et, Al.

PA Polska Akademia Nauk, Instytut Chemii Organicznej, Pol.

SO Pol., 4 pp.

CODEN: POXXA7

DT Patent

LA Polish

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	PL 163399	B1	19940331	PL 1990-287590	19901031

OS CASREACT 123:55587

GI For diagram(s), see printed CA Issue.

AB The 3rd-generation antibiotic ceftriaxone (I) and/or its tautomers are prep'd. by reaction of cephalosporanic acid deriv. II with triazinethiol deriv. III and/or its tautomers, in an org. solvent and in the presence of a Lewis acid catalyst at -10.degree. to +40.degree., followed by known isolation methods (esp. aq. diln., pH adjustment, and filtration). Suitable Lewis acids include halides of Zn, Sn, Ti, B, or Al, free or as complexes with electron

donors

such as ethers, amines, or amides. For example, 20 mL BF3.OEt2 was added dropwise to a suspension of 10 g II and 5 g III in 40 mL MeCN, and the mixt. was stirred at 0.degree. for 60 min, poured into ice-water, and neutralized to pH 7 with aq. NH3. Decolorization with active C, acidification to pH 2.7-3.0 with 1:1 HCl, filtration, etc., gave I. Ten addnl. example runs are described, with yields of 10-66%, the latter case using BF3.OEt2 in EtOAc in the presence of DMF at 20.degree..

L8 ANSWER 8 OF 12 CAPLUS COPYRIGHT 2001 ACS

AN 1989:523842 CAPLUS

DN 111:123842

TI Photoresist for forming pattern with reticulation-resistant surface layer

IN Fisher, Thomas A.

PA Shipley Co., Inc., USA

SO Eur. Pat. Appl., 9 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 309682	A2	19890405	EP 1988-112223	19880728
	EP 309682	A3	19901227		
	R: DE, FR, GB, IT				
	US 4873176	A	19891010	US 1987-90753	19870828
	JP 01128062	A2	19890519	JP 1988-214756	19880829

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US 5538820	A 19960723	US 1993-108777	19930818
PRAI US 1987-90753	19870828		
US 1988-288221	19881222		
US 1990-617967	19901121		

AB A method for forming a photoresist mask on a substrate (i.e. integrate circuit substrate) resistant to reticulation during plasma etching comprises the steps of forming an imaged and developed pos.-working photoresist layer comprising a novolak resin, an o-quinonediazidesulfonic acid ester, and an unreacted acid-activated crosslinking agent and subjecting the substrate to an etching plasma in a gaseous stream contg. a **Lewis acid**. Contact of the surface of the developed photoresist film with the **Lewis acid** causes crosslinking of the surface of the developed photoresist film during plasma etching with the formation of a reticulation-resistant surface layer. Thus, a photoresist compn. comprised of a novolak resin,

a

1-oxo-2-diazonaphthoquinone-5-arylsulfonate, a dye, a leveling agent, an adhesion promoter, and hexamethoxymethylmelamine was coated on an Al substrate, baked, imagewise exposed to a Hg lamp, developed, and plasma etched using a gas mixt. of Cl₂, CHCl₃, and BF₃ with H₂ as the carrier gas to give a wafer having a surface free of reticulation.

L8 ANSWER 9 OF 12 CAPLUS COPYRIGHT 2001 ACS

AN 1989:192953 CAPLUS

DN 110:192953

TI Halocyclogermazanes. Effect of the halo substituent on the existence of a cyclogermazane-germaimine equilibrium

AU Riviere-Baudet, M.; Khallaayoun, A.; Satge, J.

CS Lab. Chim. Organomineraux, Univ. Paul Sabatier, Toulouse, 31602, Fr.

SO Recl. Trav. Chim. Pays-Bas (1988), 107(3), 152-9

CODEN: RTCPA3; ISSN: 0165-0513

DT Journal

LA French

OS CASREACT 110:192953

AB Studies of ring opening of chlorocyclotrigermazanes in cycloaddn. reactions with the nitrones phenyl- and tert-butylbenzylideneamine N-oxide, catalyzed by Lewis bases (HMPA) or Lewis acids (ZnCl₂, M(CO)₆, M(CO)₅.cntdot.THF, M = Cr, W), show that hexachlorocyclotrigermazanes are much less reactive than the corresponding methylcyclogermazane. The decreased reactivity is attributed to the tendency of the electron-attracting chlorine atoms to promote the back-donation of electrons from nitrogen to germanium, thereby rendering the Ge-N bond

less

polar and therefore less susceptible to coordination (either with Lewis acids or Lewis bases) and attack by polar reagents such as carbonyl compds.

L8 ANSWER 10 OF 12 CAPLUS COPYRIGHT 2001 ACS

AN 1987:599926 CAPLUS

DN 107:199926

TI Adhesives for metal-plated laminates

IN Maeda, Masanori; Otsuka, Nobuyuki

PA Matsushita Electric Works, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 2 pp.

CODEN: JKXXAF

DT Patent

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LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 62132986	A2	19870616	JP 1985-274081	19851204
AB	The title adhesives, with good storage stability, comprise epoxy resins, melamine resins, poly(vinyl butyral) (I), isocyanates, Lewis acid catalysts, and org. solvents contg. cyclohexanone (II). Thus, 2 parts Epikote 153 was mixed with melamine resin 7, I 10, isocyanate 1, BF3-400 (BF3-monoethylamine complex) 0.02, II 15, MEK 40, and MeOH 24.98 parts to give an adhesive, which showed gel time just after prepn. 215 s, after 30 days storage at 40.degree. 215 s. A phenolic resin-impregnated laminate was bonded with Cu foil with the adhesive to give a sample showing soft solder heat resistance just after prepn. 30 s, after 30 days storage at 40.degree. 30 s, vs. 30 s, 9 s, resp. without II, which showed gel time just after prepn. 210 s, after 30 days storage at 40.degree. 540 s.				

L8 ANSWER 11 OF 12 CAPLUS COPYRIGHT 2001 ACS

AN 1985:78246 CAPLUS

DN 102:78246

TI Chemometrics of basicity. 1. Comparison of the basicity of o-, m-, and p-substituted pyridines toward boron trifluoride and methanol

AU Berthelot, Michel; Gal, Jean Francois; Laurence, Christian; Maria, Pierre Charles

CS Lab. Spectrochim. Mol., Univ. Nantes, Nantes, 44072, Fr.

SO J. Chim. Phys. Phys.-Chim. Biol. (1984), 81(5), 327-31

CODEN: JCPBAN; ISSN: 0021-7689

DT Journal

LA French

AB For BF3 or MeOH complexes with pyridines, the enthalpy of **complex** formation with BF3 is linearly correlated to the shift of the hydroxyl stretching vibration of MeOH. This correlation is obeyed by all meta substituents but only by -R para substituents. The + R para-substituted pyridines appear relatively more basic towards BF3, whereas ortho-substituted pyridines appear relatively more basic towards MeOH. Therefore the variable resonance effects of + R substituents and the steric effects of ortho-substituents prevent the definition of a general basicity scale. The range of validity of DN, B, or .beta. scales should be restricted as soon as the basicity-dependent property is obtained from a **Lewis acid** differing in strength or steric requirement from those used in the definitions.

L8 ANSWER 12 OF 12 CAPLUS COPYRIGHT 2001 ACS

AN 1978:482980 CAPLUS

DN 89:82980

TI Polymerized vinyl carbazoles sensitized by nitro-substituted 9-dicyanomethylene fluorenes

IN Hoegl, Helmut; Barchietto, Giacomo

PA Xerox Corp., USA

SO U.S., 12 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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V. Balasubramanian

PI US 4069046 A 19780117 US 1974-437573 19740129
PRAI US 1967-652278 19670710
US 1971-116989 19710219
AB A photoconductive insulating coating material for electrophotog. plates
is
comprised of a charge-transfer **complex** prep'd. from an arom.
resin and a nitro-substituted 9-dicyanomethylenefluorene. The arom.
resin
is selected from poly(N-vinylcarbazole), styrene resins, phenol-aldehyde
resins, polycarbonates, epoxy resins, phenoxy resins, and polyurethanes.
Thus, a polyphenylene oxide resin (PPO-531, General Elec. Co.) 4 parts
was
dissolved in C6H4Cl2 50 parts. To this soln. was added a soln. comprised
of 9-dicyanomethylene-2,4,5,7-tetranitrofluorene 1, cyclohexanone 10, and
C6H4Cl2 20 parts. The resulting soln. was then coated to a 7-.mu.
thickness on a 5-mil Al plate by flow coating, dried, and used at
100.degree. for 30 min. The plate was charged to -600 V by means of a
corona discharge, exposed by projection at 180 ft-candle-s, and cascade
developed. The developed image was then electrostatically transferred to
a receiving sheet and fused thereon.

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NEWS	5	Oct 27 Patent Assignee Code Dictionary now available in Derwent Patent Files
NEWS	6	Oct 27 Plasdoc Key Serials Dictionary and Echoing added to Derwent Subscriber Files WPIDS and WPIX
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NEWS	10	Dec 15 2001 STN Pricing
NEWS	11	Dec 17 Merged CEABA-VTB for chemical engineering and biotechnology
NEWS	12	Dec 17 Corrosion Abstracts on STN
NEWS	13	Dec 17 SYNTHLINE from Prous Science now available on STN
NEWS	14	Dec 17 The CA Lexicon available in the CAPLUS and CA files
NEWS	15	Jan 05 AIDSILINE is being removed from STN
NEWS	16	Feb 06 Engineering Information Encompass files have new names
NEWS	17	Feb 16 TOXLINE no longer being updated
NEWS EXPRESS		FREE UPGRADE 5.0e FOR STN EXPRESS 5.0 WITH DISCOVER! (WINDOWS) NOW AVAILABLE
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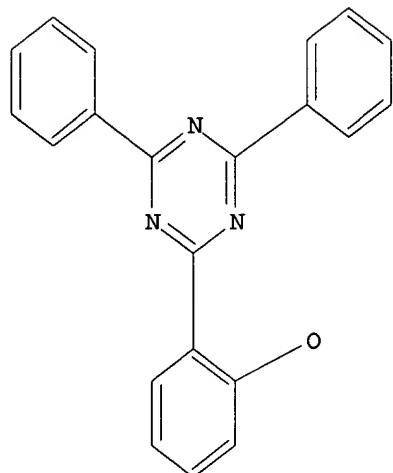
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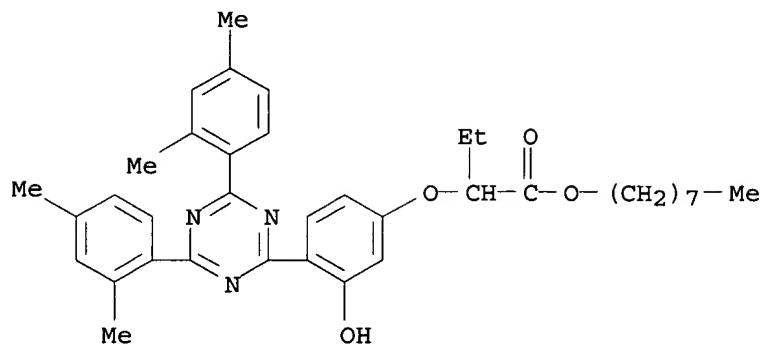
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PROJECTED ANSWERS: 981 TO 2019

L3 50 SEA SSS SAM L1

=> d scan l3

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Butanoic acid, 2-[4-[(4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-, octyl ester (9CI)
MF C37 H45 N3 O4

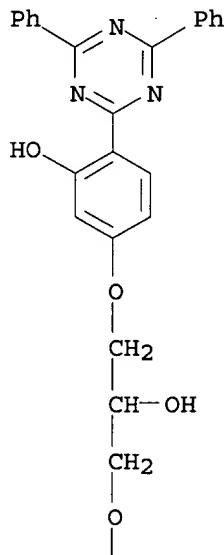
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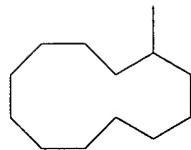


HOW MANY MORE ANSWERS DO YOU WISH TO SCAN? (1):49

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 5-[3-(cyclododecyloxy)-2-hydroxypropoxy]-2-(4,6-diphenyl-1,3,5-triazin-2-yl) - (9CI)
MF C36 H43 N3 O4

PAGE 1-A

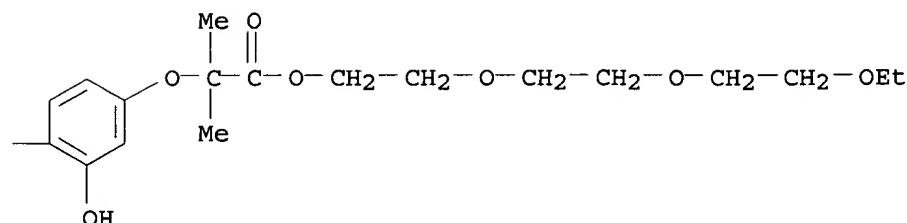
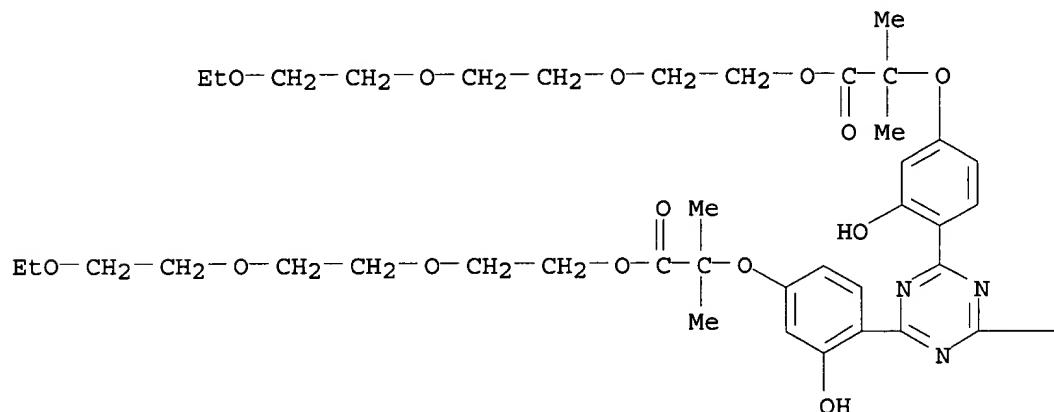




L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS

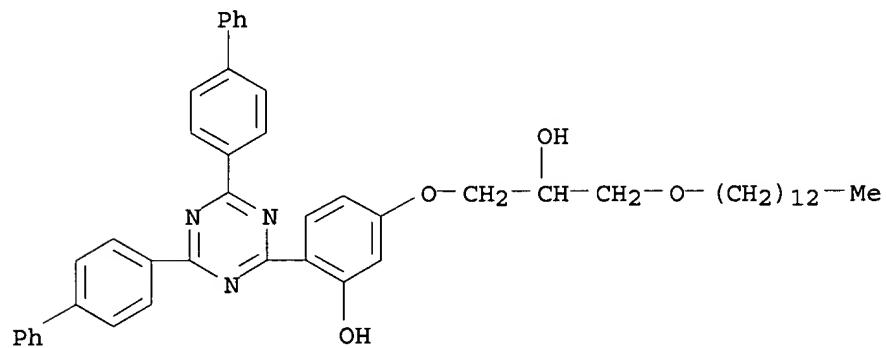
IN Propanoic acid, 2,2',2''-[1,3,5-triazine-2,4,6-triyltris[(3-hydroxy-4,1-phenyleneoxy)]tris[2-methyl-, tris[2-[2-(2-ethoxyethoxyethoxy]ethyl]ester (9CI)

MF C57 H81 N3 O21



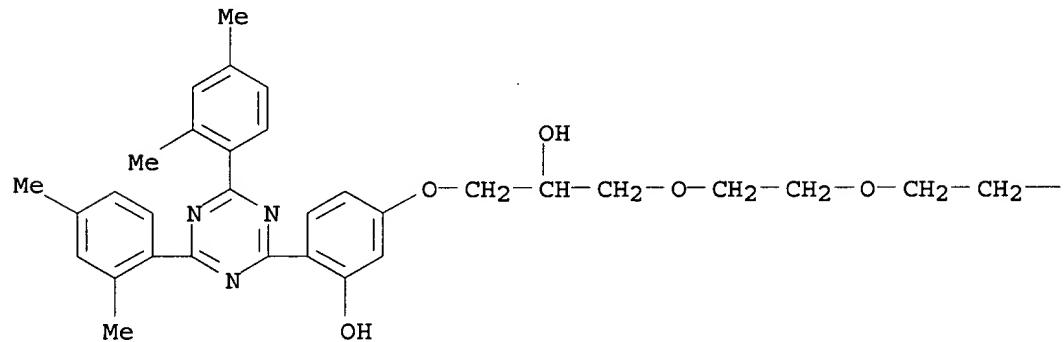
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L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol,
2-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-5-[2-hydroxy-
3-(tridecyloxy)propoxy] - (9CI)
MF C49 H55 N3 O4
CI COM



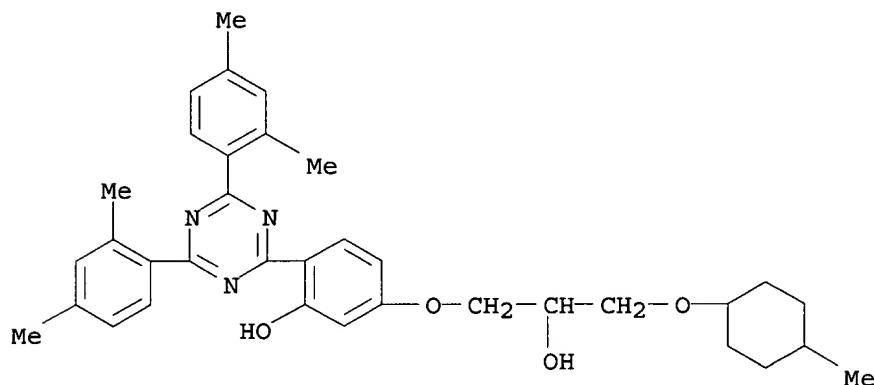
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 2,5,8,11-Tetraoxatetradecan-13-ol, 14-[4-[4,6-bis(2,4-dimethylphenyl)-
1,3,5-triazin-2-yl]-3-hydroxyphenoxy] - (9CI)
MF C35 H43 N3 O7

PAGE 1-A



— O—CH₂—CH₂—OMe

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol,
2-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-5-[2-hydroxy-3-
[(4-methylcyclohexyl)oxy]propoxy] - (9CI)
MF C₃₅ H₄₁ N₃ O₄

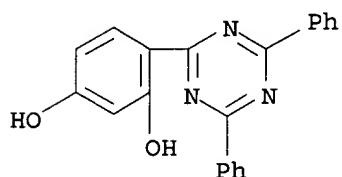


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Hiwax 1105A, ester with 4-(4,6-diphenyl-1,3,5-triazin-2-yl)-1,3-
benzenediol (9CI)
MF C₂₁ H₁₅ N₃ O₂ . x Unspecified

CM 1

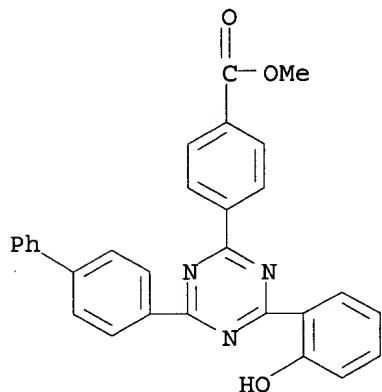
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CM 2



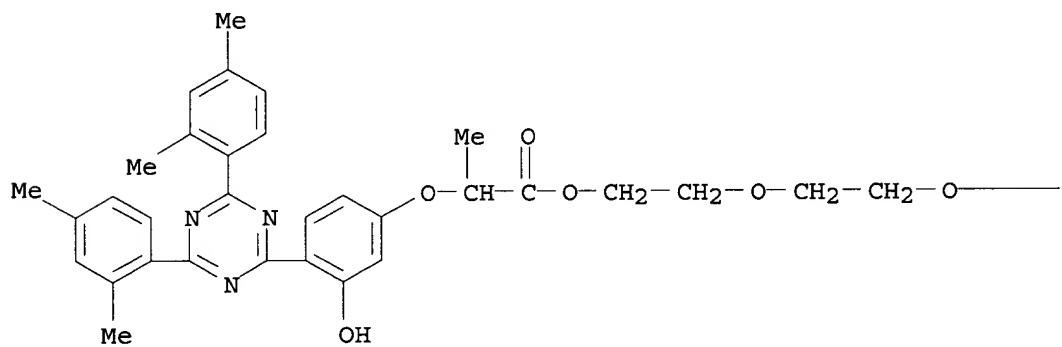
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L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Benzoic acid,
4-[4-[1,1'-biphenyl]-4-yl-6-(2-hydroxyphenyl)-1,3,5-triazin-2-yl]-, methyl ester (9CI)
MF C29 H21 N3 O3



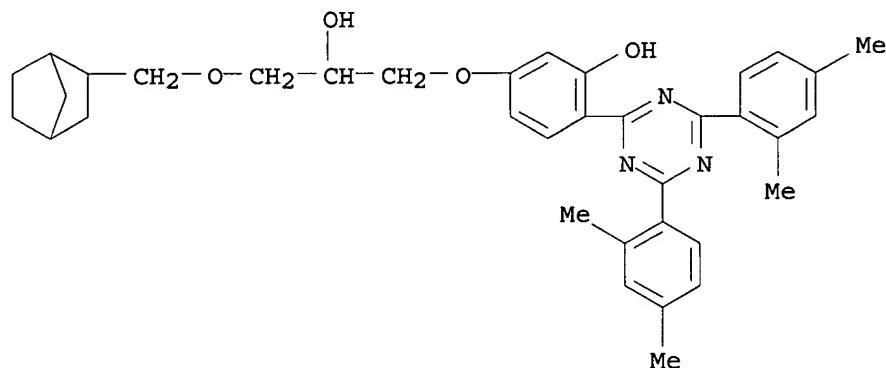
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Propanoic acid, 2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-, 2-[2-(2-butoxyethoxy)ethoxy]ethyl ester (9CI)
MF C38 H47 N3 O7

PAGE 1-A

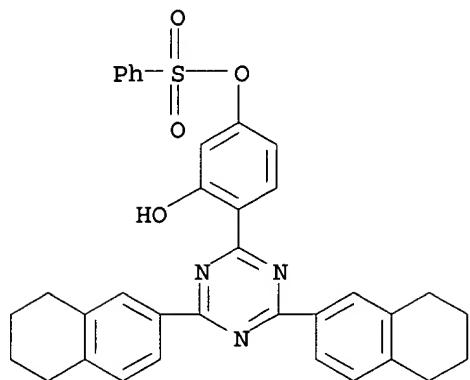


— CH₂—CH₂—OBu-n

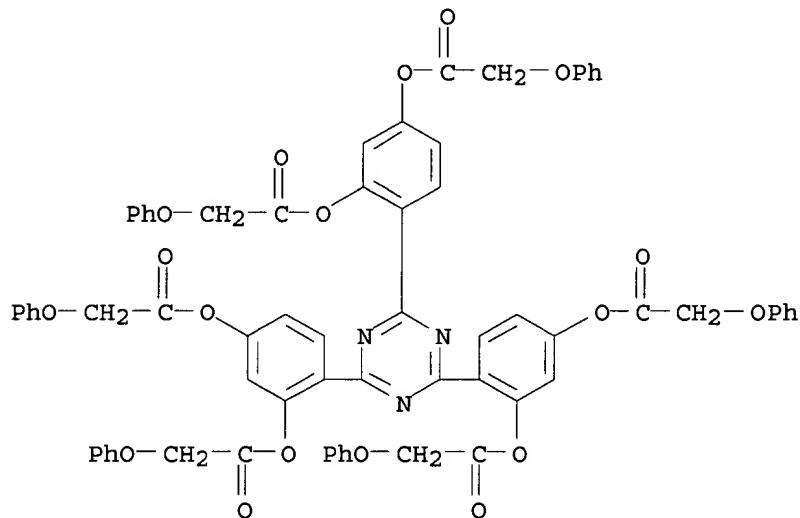
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 5-[3-(bicyclo[2.2.1]hept-2-ylmethoxy)-2-hydroxypropoxy]-2-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]- (9CI)
MF C36 H41 N3 O4



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 1,3-Benzenediol, 4-[4,6-bis(5,6,7,8-tetrahydro-2-naphthalenyl)-1,3,5-triazin-2-yl]-, 1-benzenesulfonate (9CI)
MF C35 H31 N3 O4 S

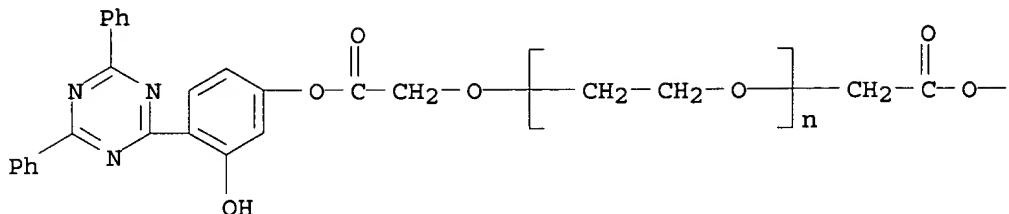


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Acetic acid, phenoxy-, 1,3,5-triazine-2,4,6-triyltri-1,2,4-benzenetriyl ester (9CI)
MF C69 H51 N3 O18

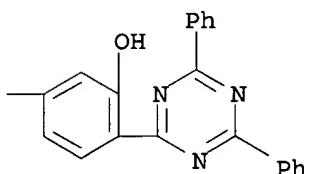


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Poly(oxy-1,2-ethanediyl),
.alpha.-[2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-
3-hydroxyphenoxy]-2-oxoethyl]--omega.-[2-[4-(4,6-diphenyl-1,3,5-triazin-2-
yl)-3-hydroxyphenoxy]-2-oxoethoxy] - (9CI)
MF (C₂ H₄ O)_n C₄₆ H₃₂ N₆ O₇
CI PMS

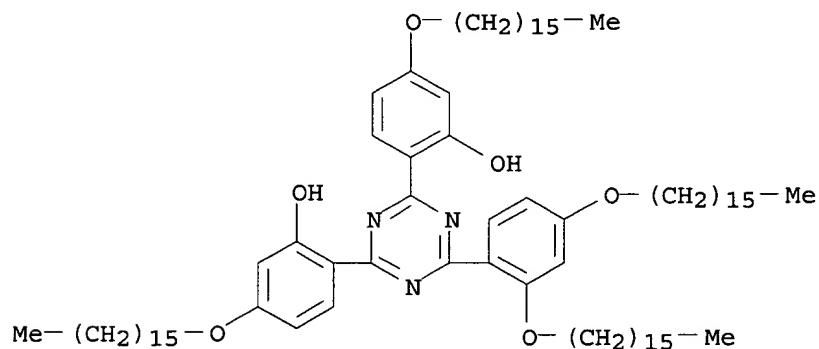
PAGE 1-A



PAGE 1-B



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN Phenol, 2,2'-(6-[2,4-bis(hexadecyloxy)phenyl]-1,3,5-triazine-2,4-diyl)bis[5-(hexadecyloxy)- (9CI)
 MF C85 H143 N3 O6

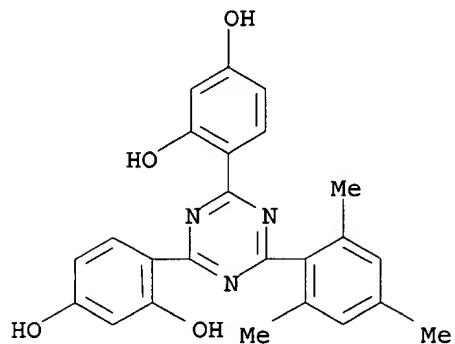


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN 1,3-Benzenedicarboxylic acid, polymer with 2,2-dimethyl-1,3-propanediol, 2-ethyl-2-(hydroxymethyl)-1,3-propanediol, hexanedioic acid, 3-hydroxy-2-(hydroxymethyl)-2-methylpropanoic acid, 12-hydroxyoctadecanoic acid, methyl 2-methyl-2-propenoate, 2-methyl-2-propenoic acid, oxiranylmethyl 2-methyl-2-propenoate and 4,4'-(6-(2,4,6-trimethylphenyl)-1,3,5-triazine-2,4-diyl)bis[1,3-benzenediol] (9CI)

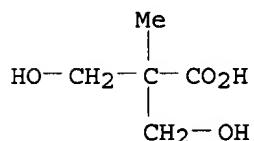
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MF (C₂₄ H₂₁ N₃ O₄ . C₁₈ H₃₆ O₃ . C₈ H₆ O₄ . C₇ H₁₀ O₃ . C₆ H₁₄ O₃ . C₆ H₁₀ O₄ . C₅ H₁₂ O₂ . C₅ H₁₀ O₄ . C₅ H₈ O₂ . C₄ H₆ O₂)_x
CI PMS

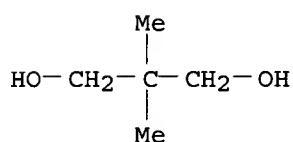
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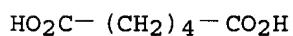
CM 2



CM 3

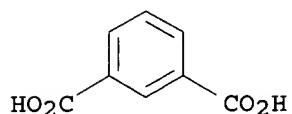


CM 4

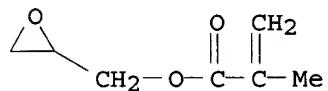


CM 5

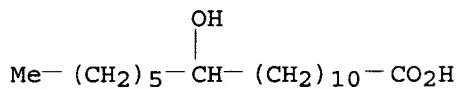
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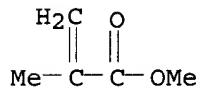
CM 6



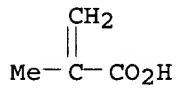
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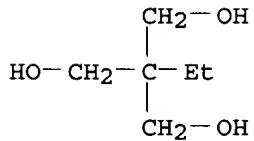
CM 8



CM 9

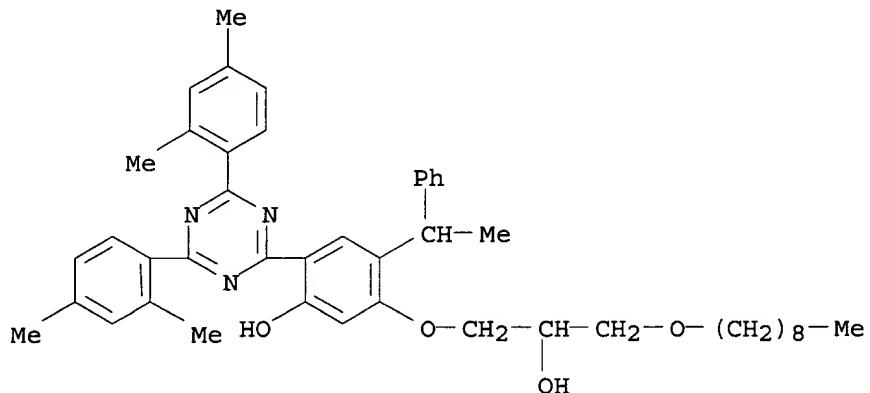


CM 10



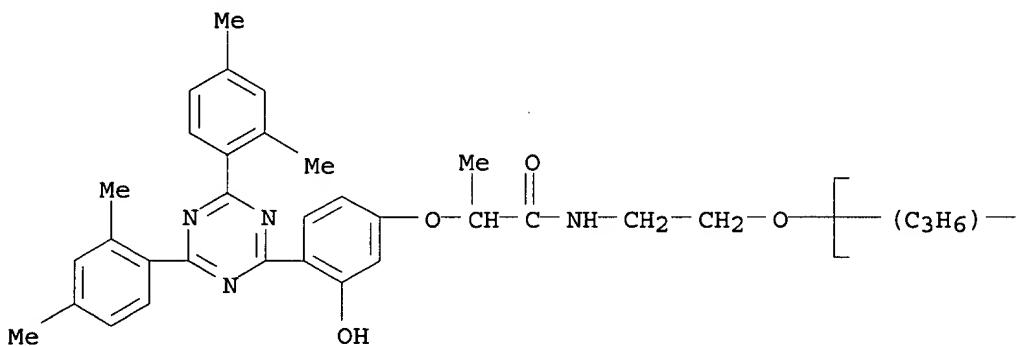
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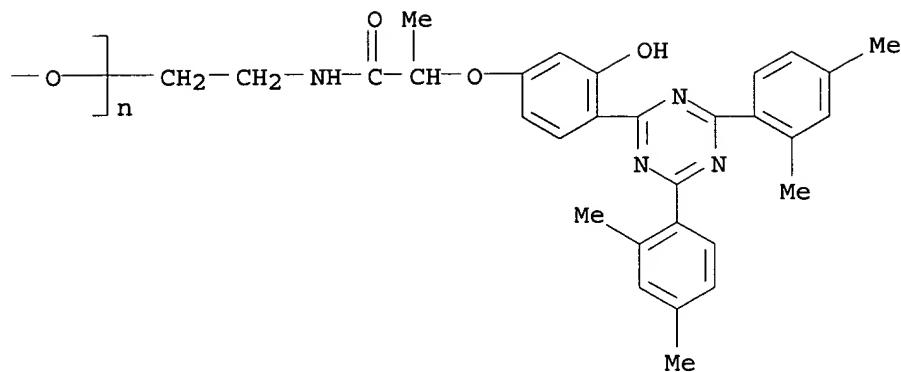
IN Phenol,
2-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-5-[2-hydroxy-3-(nonyloxy)propoxy]-4-(1-phenylethyl)- (9CI)
MF C45 H55 N3 O4



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Poly[oxy(methyl-1,2-ethanediyl)], .alpha.-[2-[2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-1-oxopropyl]amino]methylethyl]-.omega.-[2-[2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-1-oxopropyl]amino]methylethoxy]- (9CI)
MF (C₃ H₆ O)_n C₆₂ H₆₆ N₈ O₇
CI IDS, PMS

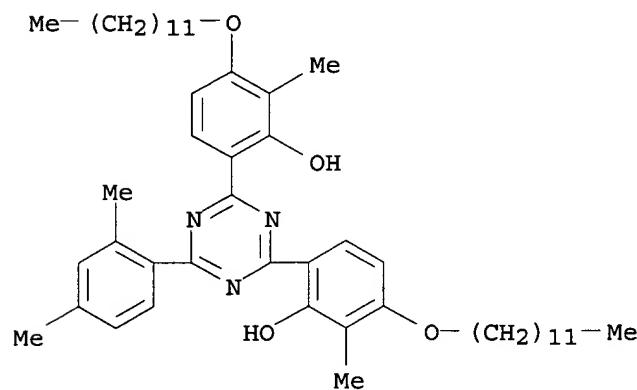
PAGE 1-A





2 (D1-Me)

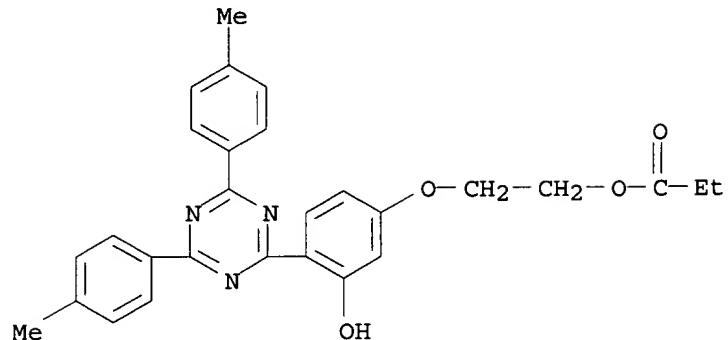
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2,2'-[6-(2,4-dimethylphenyl)-1,3,5-triazine-2,4-diyl]bis[5-(dodecyloxy)-6-methyl- (9CI)
MF C49 H71 N3 O4



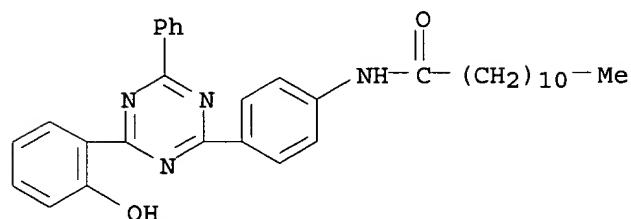
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2-[4,6-bis(4-methylphenyl)-1,3,5-triazin-2-yl]-5-[2-(1-

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oxopropoxy)ethoxy] - (9CI)
MF C28 H27 N3 O4

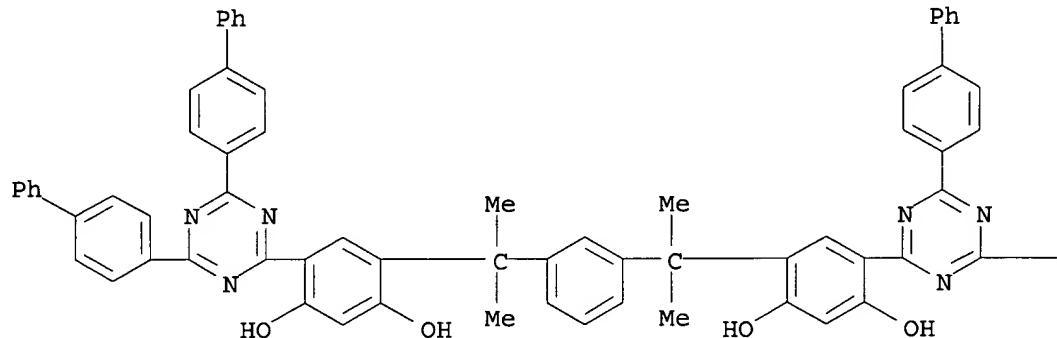


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Dodecanamide, N-[4-[4-(2-hydroxyphenyl)-6-phenyl-1,3,5-triazin-2-yl]phenyl] - (9CI)
MF C33 H38 N4 O2

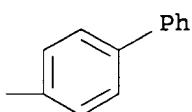


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 1,3-Benzenediol, 4,4'-(1,3-phenylenebis(1-methylethylidene))bis[6-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl] - (9CI)
MF C78 H60 N6 O4

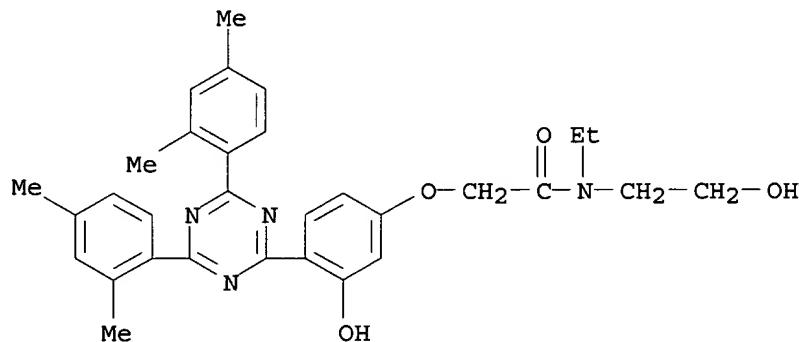
PAGE 1-A



PAGE 1-B



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Acetamide, 2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-N-ethyl-N-(2-hydroxyethyl)- (9CI)
MF C31 H34 N4 O4

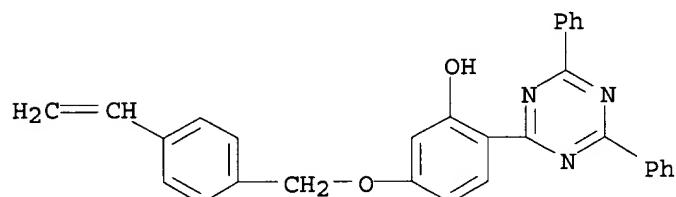


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 2-Propenoic acid, butyl ester, polymer with
2-(4,6-diphenyl-1,3,5-triazin-2-yl)-5-[(3-ethenylphenyl)methoxy]phenol and
2-(4,6-diphenyl-1,3,5-triazin-

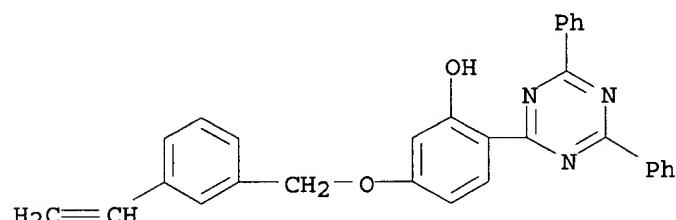
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2-yl)-5-[(4-ethenylphenyl)methoxy]phenol (9CI)
MF (C₃₀ H₂₃ N₃ O₂ · C₃₀ H₂₃ N₃ O₂ · C₇ H₁₂ O₂)_x
CI PMS

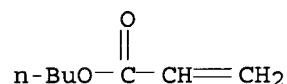
CM 1



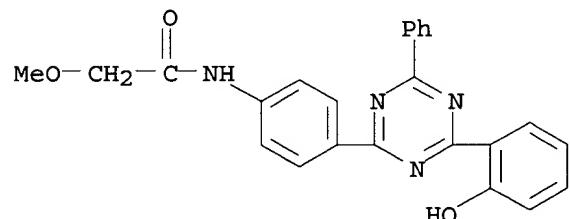
CM 2



CM 3



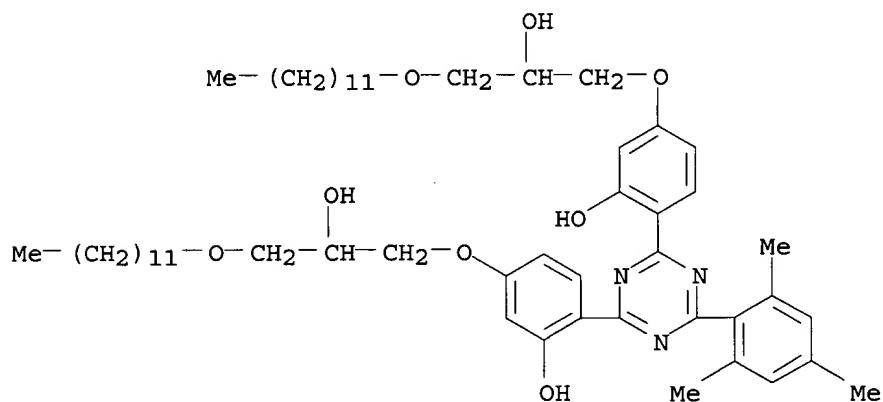
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Acetamide,
N-[4-[4-(2-hydroxyphenyl)-6-phenyl-1,3,5-triazin-2-yl]phenyl]-2-methoxy- (9CI)
MF C₂₄ H₂₀ N₄ O₃



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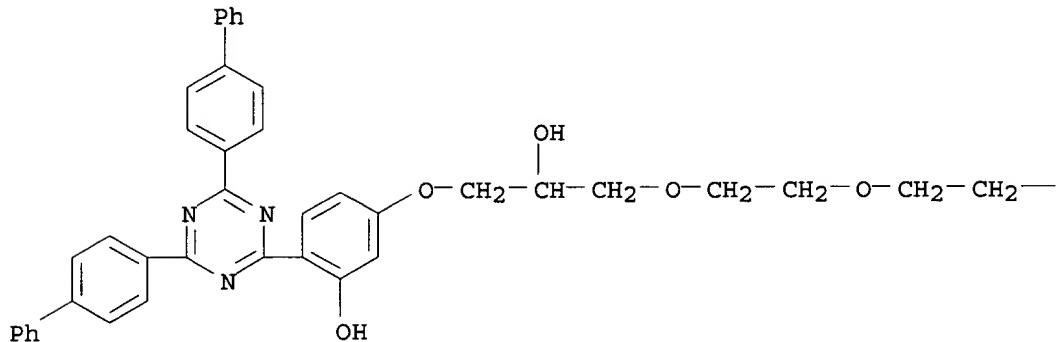
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN 4,7,10,13-Tetraoxaheptadecan-2-ol, 1-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-, mixt. with 2,2'-[6-(2,4,6-trimethylphenyl)-1,3,5-triazine-2,4-diyl]bis[5-[3-(dodecyloxy)-2-hydroxypropoxyl]phenol] (9CI)
 MF C54 H81 N3 O8 . C46 H49 N3 O7
 CI MXS

CM 1



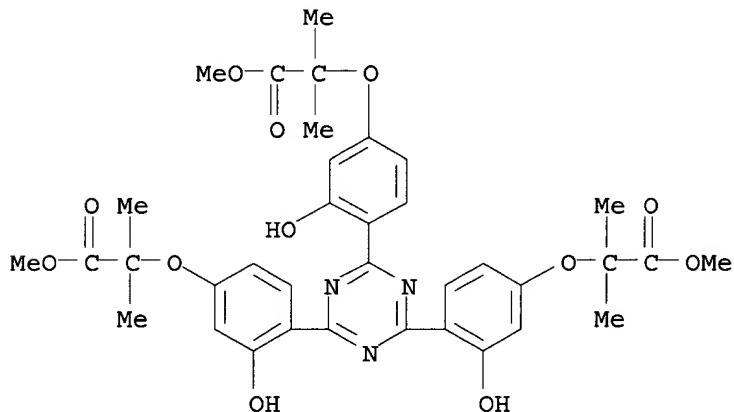
CM 2

PAGE 1-A



— O—CH₂—CH₂—OBu-n

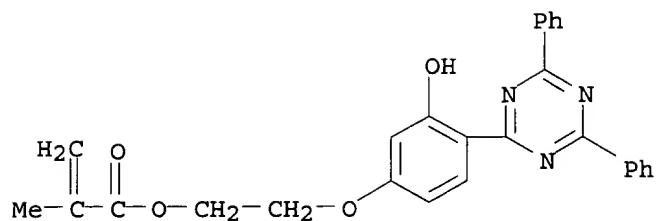
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Propanoic acid, 2,2',2'''-[1,3,5-triazine-2,4,6-triyltris[(3-hydroxy-4,1-phenylene)oxy]]tris[2-methyl-, trimethyl ester (9CI)
MF C36 H39 N3 O12



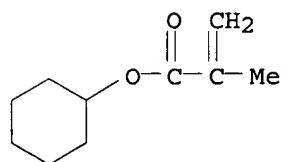
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with cyclohexyl 2-methyl-2-propenoate, 2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]ethyl 2-methyl-2-propenoate, methyl 2-methyl-2-propenoate, methyl 2-propenoate and 2-propenoic acid (9CI)
MF (C₂₇ H₂₃ N₃ O₄ . C₁₀ H₁₆ O₂ . C₈ H₁₄ O₂ . C₅ H₈ O₂ . C₄ H₆ O₂ . C₃ H₄ O₂)_x
CI PMS

CM 1

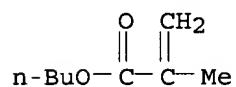
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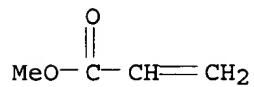
CM 2



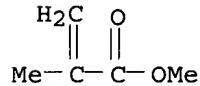
CM 3



CM 4

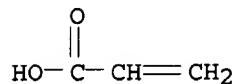


CM 5

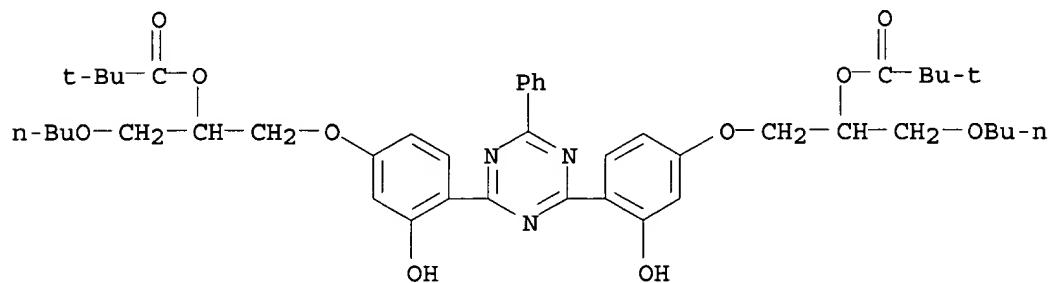


CM 6

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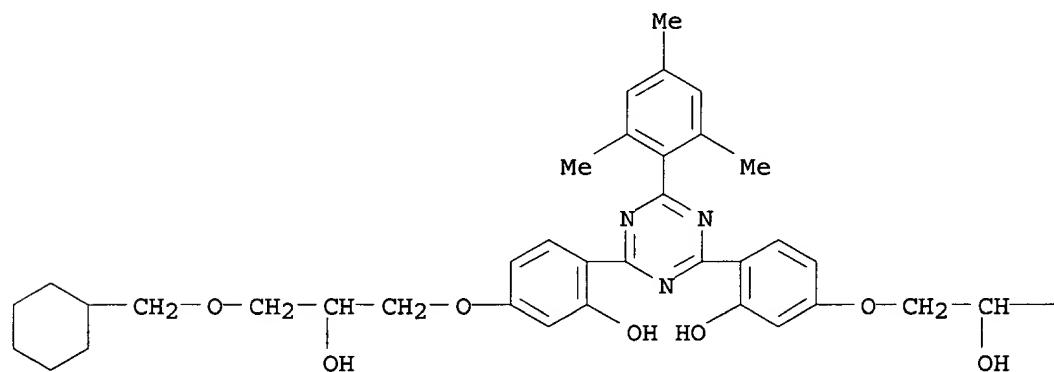


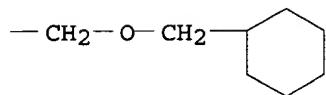
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Propanoic acid, 2,2-dimethyl-, (6-phenyl-1,3,5-triazine-2,4-diyl)bis[(3-hydroxy-4,1-phenylene)oxy[1-(butoxymethyl)-2,1-ethanediyl]] ester (9CI)
MF C45 H59 N3 O10



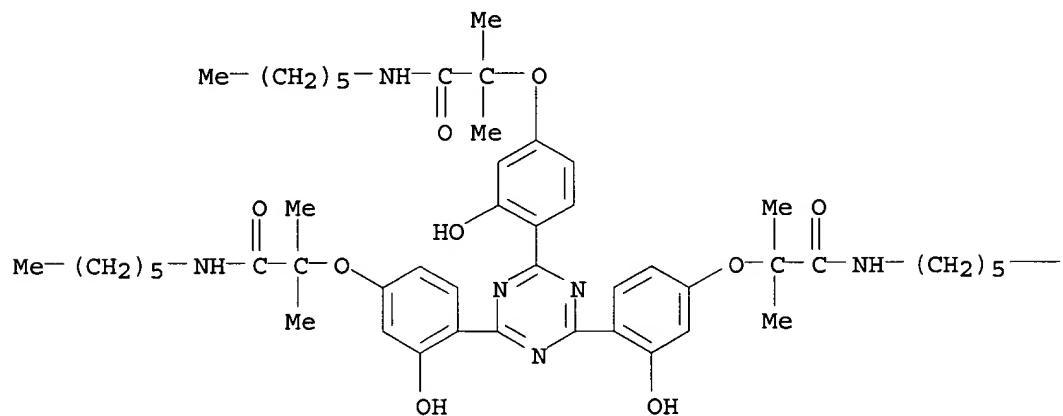
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2,2'-[6-(2,4,6-trimethylphenyl)-1,3,5-triazine-2,4-diyl]bis[5-[3-(cyclohexylmethoxy)-2-hydroxypropoxy]- (9CI)
MF C44 H57 N3 O8

PAGE 1-A



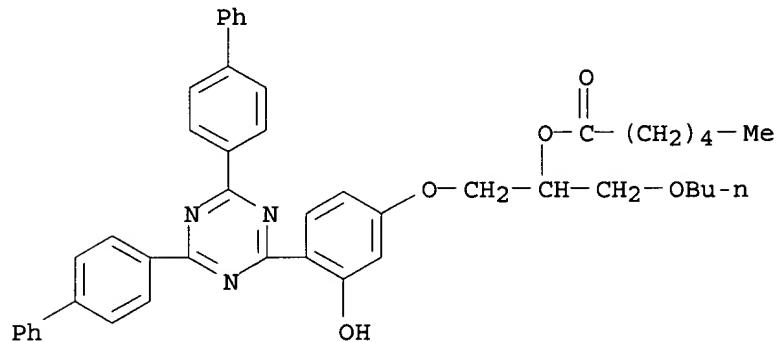


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Propanamide, 2,2',2'''-[1,3,5-triazine-2,4,6-triyltris[(3-hydroxy-4,1-phenylene)oxy]]tris[N-hexyl-2-methyl- (9CI)
MF C51 H72 N6 O9

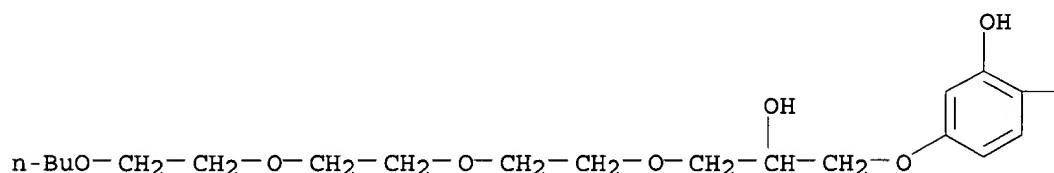


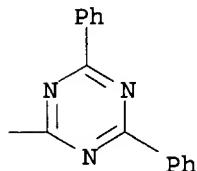
— Me

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Hexanoic acid, 2-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]-1-(butoxymethyl)ethyl ester (9CI)
MF C46 H47 N3 O5

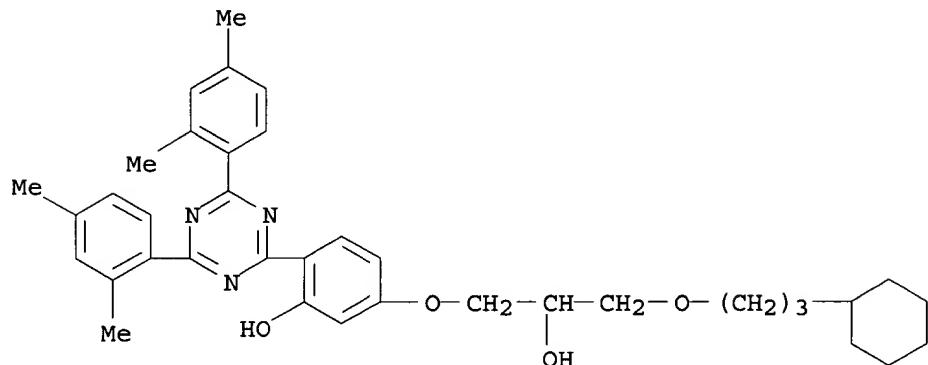


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 4,7,10,13-Tetraoxaheptadecan-2-ol,
1-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-
3-hydroxyphenoxy]- (9CI)
MF C34 H41 N3 O7

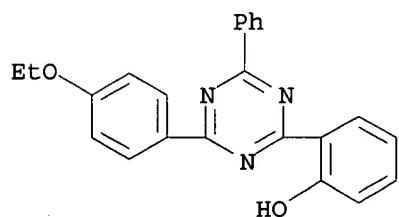




L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-5-[3-(3-cyclohexylpropoxy)-2-hydroxypropoxy]- (9CI)
MF C37 H45 N3 O4

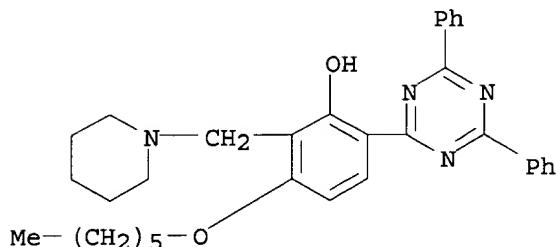


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2-[4-(4-ethoxyphenyl)-6-phenyl-1,3,5-triazin-2-yl]- (9CI)
MF C23 H19 N3 O2



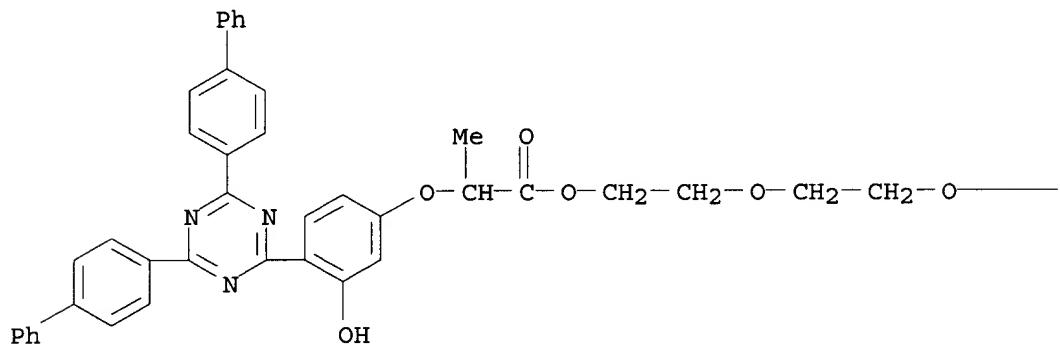
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 6-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-(hexyloxy)-2-(1-piperidinylmethyl)- (9CI)
MF C33 H38 N4 O2

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L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Propanoic acid,
2-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-
hydroxyphenoxy]-, 2-[2-(2-methoxyethoxy)ethoxy]ethyl ester (9CI)
MF C₄₃ H₄₁ N₃ O₇

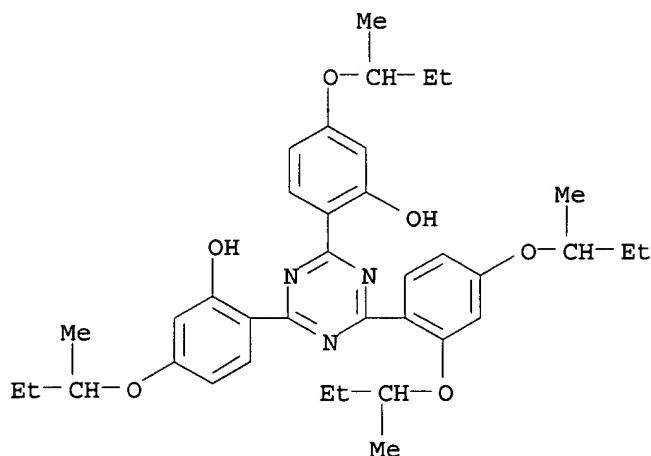
PAGE 1-A



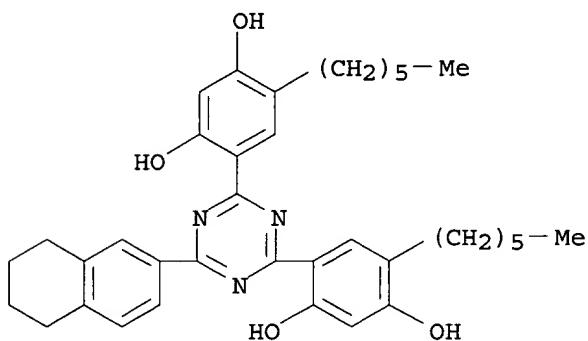
PAGE 1-B

—CH₂—CH₂—OMe

L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2,2'-(6-[2,4-bis(1-methylpropoxy)phenyl]-1,3,5-triazine-2,4-
diyl)bis[5-(1-methylpropoxy)- (9CI)
MF C₃₇ H₄₇ N₃ O₆



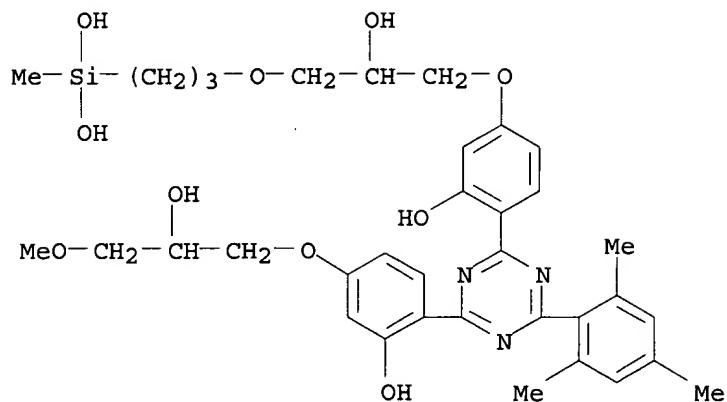
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN 1,3-Benzenediol, 4,4'-[6-(5,6,7,8-tetrahydro-2-naphthalenyl)-1,3,5-triazine-2,4-diyl]bis[6-hexyl- (9CI)
 MF C37 H45 N3 O4



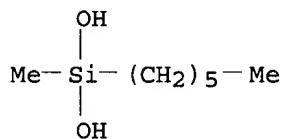
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN Silanediol, hexylmethyl-, polymer with
 [3- [2-hydroxy-3- [3-hydroxy-4- [4- [2-
 hydroxy-4- (2-hydroxy-3-methoxypropoxy)phenyl]-6- (2,4,6-trimethylphenyl)-
 1,3,5-triazin-2-yl]phenoxy]propoxy]propyl]methylsilanediol (9CI)
 MF (C35 H45 N3 O10 Si . C7 H18 O2 Si)x
 CI PMS

CM 1

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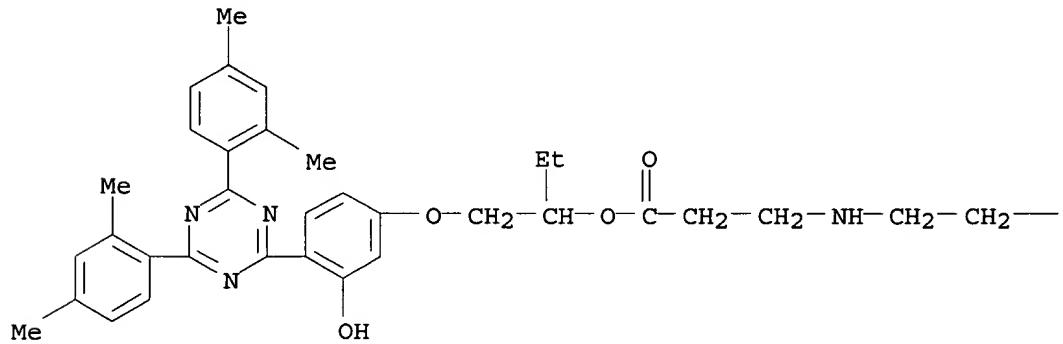


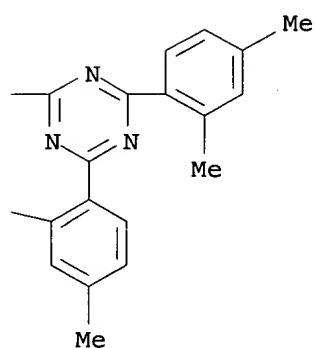
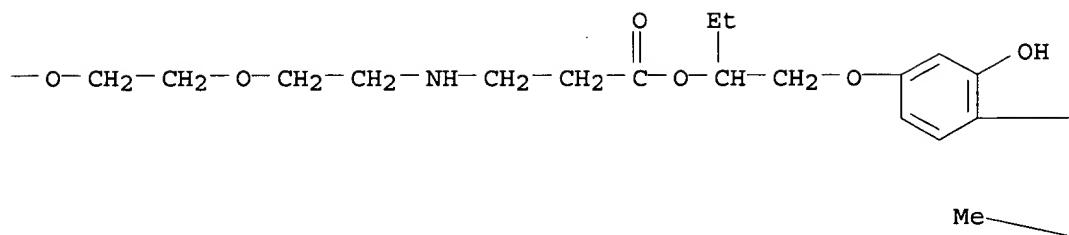
CM 2



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 7,10-Dioxa-4,13-diazahexadecanedioic acid, bis[1-[[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]methyl]propyl] ester (9CI)
MF C70 H82 N8 O10

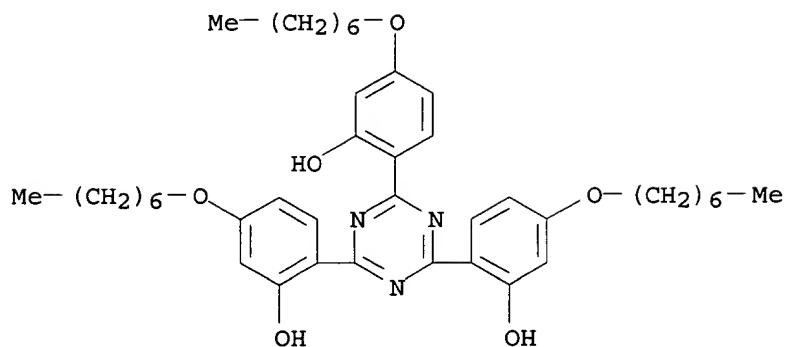
PAGE 1-A



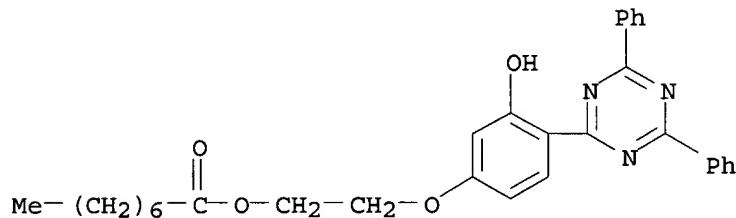


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 2,2',2'''-(1,3,5-triazine-2,4,6-triyl)tris[5-(heptyloxy)-] (9CI)
MF C42 H57 N3 O6

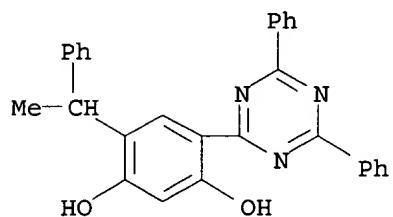
V. Balasubramanian



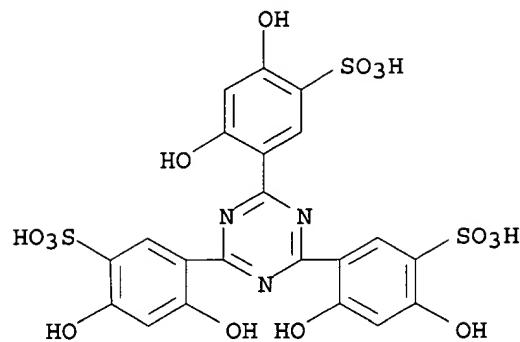
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Octanoic acid, 2-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]ethyl ester (9CI)
MF C31 H33 N3 O4



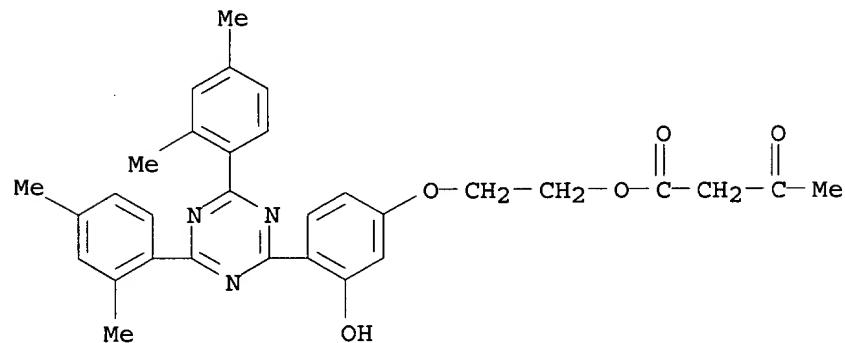
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN 1,3-Benzenediol, 4-(4,6-diphenyl-1,3,5-triazin-2-yl)-6-(1-phenylethyl)- (9CI)
MF C29 H23 N3 O2



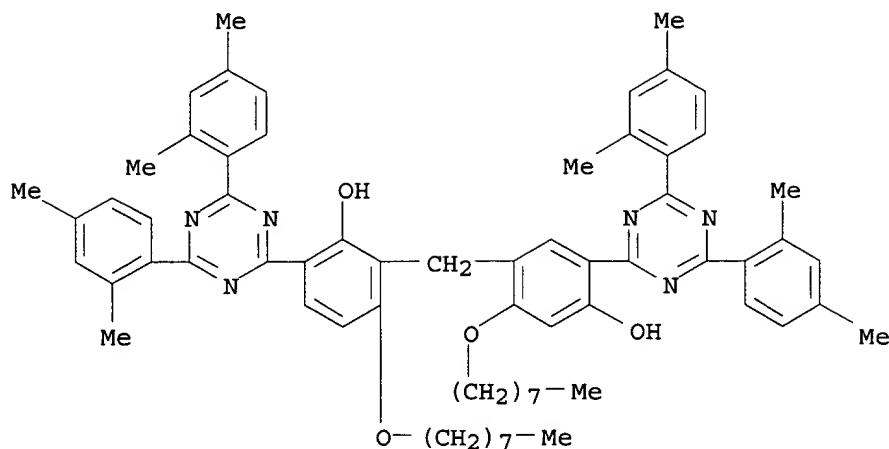
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Benzenesulfonic acid, 3,3',3'''-(1,3,5-triazine-2,4,6-triyl)tris[4,6-dihydroxy-] (9CI)
MF C21 H15 N3 O15 S3



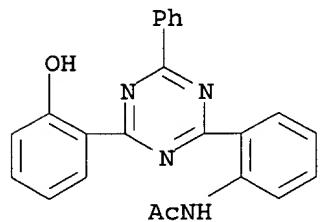
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Butanoic acid, 3-oxo-, 2-[4-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-3-hydroxyphenoxy]ethyl ester (9CI)
MF C31 H31 N3 O5



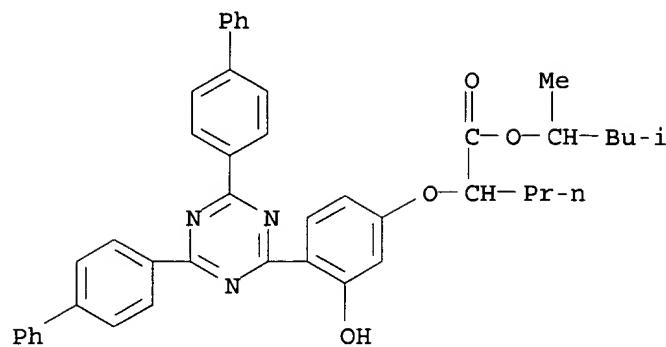
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
IN Phenol, 6-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-2-[[5-[4,6-bis(2,4-dimethylphenyl)-1,3,5-triazin-2-yl]-4-hydroxy-2-(octyloxy)phenyl]methyl]-3-(octyloxy)- (9CI)
MF C67 H78 N6 O4



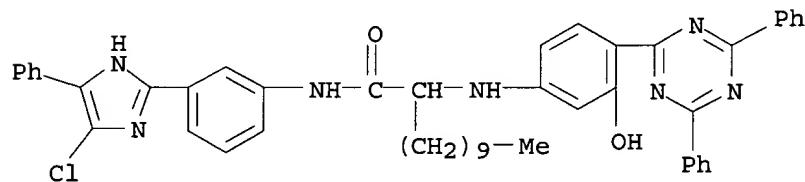
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN Acetamide, N-[2-[4-(2-hydroxyphenyl)-6-phenyl-1,3,5-triazin-2-yl]phenyl]-
 (9CI)
 MF C23 H18 N4 O2



L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN Pentanoic acid,
 2-[4-[4,6-bis([1,1'-biphenyl]-4-yl)-1,3,5-triazin-2-yl]-3-
 hydroxyphenoxy]-, 1,3-dimethylbutyl ester (9CI)
 MF C44 H43 N3 O4

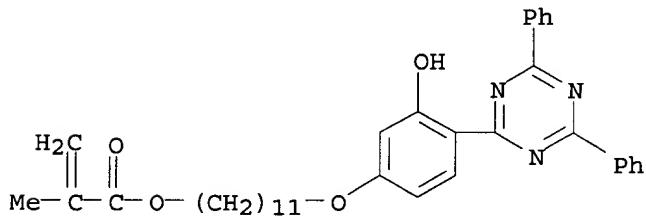


L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN Dodecanamide,
 N-[3-(4-chloro-5-phenyl-1H-imidazol-2-yl)phenyl]-2-[(4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenyl)amino]- (9CI)
 MF C48 H48 Cl N7 O2



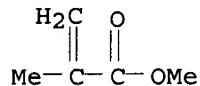
L3 50 ANSWERS REGISTRY COPYRIGHT 2001 ACS
 IN 2-Propenoic acid, 2-methyl-, 11-[4-(4,6-diphenyl-1,3,5-triazin-2-yl)-3-hydroxyphenoxy]undecyl ester, polymer with methyl 2-methyl-2-propenoate (9CI)
 MF (C36 H41 N3 O4 . C5 H8 O2)x
 CI PMS

CM 1



CM 2

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L2 93410 L1

=> s 12 and (lewis(l)acid)
36804 LEWIS
3010872 ACID
17534 LEWIS(L)ACID
L3 105 L2 AND (LEWIS(L)ACID)

=> s 3 and Friedel(l)craft
5044811 3
13520 FRIEDEL
1400 CRAFT
546 FRIEDEL(L)CRAFT
L4 296 3 AND FRIEDEL(L)CRAFT

=> 3 and friedel
3 IS NOT A RECOGNIZED COMMAND
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"HELP COMMANDS" at an arrow prompt (=>).

=> s 3 and friedel
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L5 6974 3 AND FRIEDEL

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1400 CRAFT
546 FRIEDEL(L)CRAFT
L6 0 L3 AND FRIEDEL(L)CRAFT

=> s 13 and (cpmplex or promoter or initiator)
0 CPMLEX
113986 PROMOTER
46088 INITIATOR
L7 3 L3 AND(CPMPLEX OR PROMOTER OR INITIATOR)

=> s 13 and (complex or promoter or initiator)
951602 COMPLEX
113986 PROMOTER
46088 INITIATOR
L8 12 L3 AND (COMPLEX OR PROMOTER OR INITIATOR)

=> d bib abs 1-12

L8 ANSWER 1 OF 12 CAPLUS COPYRIGHT 2001 ACS

V. Balasubramanian

AN 2000:351512 CAPLUS

DN 132:347592

TI Preparation of 2-halo-4,6-diaryltriazines from cyanuric halides and arenes

using a combination of Lewis acids and reaction promoters.

IN Gupta, Ram B.; Jakielka, Dennis J.; Venimadhavan, Sampath; Cappadona, Russell C.; Pai, Venkatrao K.

PA Cytec Technology Corp., USA

SO PCT Int. Appl., 80 pp.

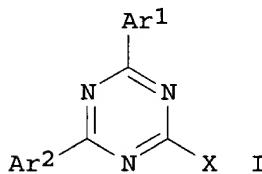
CODEN: PIXXD2

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2000029392	A1	20000525	WO 1999-US27253	19991117
	W: AE, AL, AM, AU, AZ, BA, BB, BG, BR, BY, CA, CN, CU, CZ, EE, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LV, MA, MD, MG, MK, MN, MW, MX, NO, NZ, PL, RO, RU, SD, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
	RW: GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG				
	EP 1131305	A1	20010912	EP 1999-960428	19991117
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	US 2001020094	A1	20010906	US 2001-779597	20010209
PRAI	US 1998-108786	P	19981117		
	US 1999-442000	A3	19991117		
	WO 1999-US27253	W	19991117		
OS	CASREACT 132:347592; MARPAT 132:347592				
GI					



AB Title compds. [I; Ar1, Ar2 = (substituted) Ph; X = halo], were prep'd. by reaction of arenes with cyanuric halides in the presence of a reaction facilitator comprising .gtoreq.1 Lewis acid and .gtoreq.1 reaction promoter, optionally in the presence of .gtoreq.1 solvent. Thus, cyanuric chloride and AlCl3 in PhCl at ice temp.

were treated with conc. HCl and m-xylene to give 95% 2-chloro-4,6-bis(2,4-dimethylphenyl)-1,3,5-triazine.

RE.CNT 9

RE

(1) Asahi Kasei Kogyo Kk; JP 06298674 A 1994 CAPLUS

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(2) Brunetti, H; HELVETICA CHIMICA ACTA 1972, V55(5), P1566 CAPLUS
(3) Ciba Geigy; US 5726310 A CAPLUS
(4) Ciba Geigy; EP 0779280 A 1997 CAPLUS
(5) Ciba Geigy Ag; EP 0165608 A 1985 CAPLUS
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L8 ANSWER 2 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 2000:266352 CAPLUS
DN 132:295215
TI Rapidly active energy ray-curable coating compositions and their film formation
IN Maruyama, Tsutomu; Seko, Kenji; Miyakawa, Kenji; Ichimura, Kunihiro
PA Kansai Paint Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2000119557	A2	20000425	JP 1998-292094	19981014

AB The compns. contain 100 parts melamine resin or its mixts. with acrylic resins, polyesters, and/or alkyd resins, 0.01-10 parts photocationic polymn. initiators which generate Bronsted acids or Lewis acids upon active energy ray irradn., and 0.05-10 parts acid amplifiers catalyzed by the acids generated by the photocationic initiators. Thus, a compn. contg. butylated melamine resin 167, Cyraure UVI 6990 (initiator) 1, and cis-3-(p-toluenesulfonyloxy)-2-pinanol 1 part was applied on an epoxy-primed Al sheet, UV-irradiated, and heated at 110.degree. for 15 min to form a film showing pencil hardness H and good solvent resistance.

L8 ANSWER 3 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1999:388571 CAPLUS
DN 131:80820
TI Production method of transparent hologram
IN Ito, Hiromitsu; Ohe, Yasushi
PA Toppan Printing Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 6 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 11161137	A2	19990618	JP 1997-325028	19971126

AB The method involves forming a film comprising a hologram recording material, on a substrate, contg. (A) a cationic polymerizable solvent-sol. thermosetting epoxy oligomer having .gtoreq.1 glycidyl group, (B) a radical polymerizable ethylenic unsatd. bond-contg. aliph. monomer which is liq. at room temp. and atm. and has boiling temp. .gtoreq.100.degree. at atm., (C) a photoinitiator which generates a Broensted acid or Lewis acid by chem. radiation exposure, and (D) a dye sensitizing agent, (2) holog. exposing, (3) developing, and (4)

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irradiating with a visible light with wavelength 200-800 nm at 40-150.degree.. The hologram shows high sensitivity to visible light, excellent weather and heat resistance, durability, and good holog. properties such as resoln., transparency, etc.

L8 ANSWER 4 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1999:181614 CAPLUS
DN 130:237997
TI Highly branched olefin polymers and their uses
IN Brookhart, Maurice S.; Johnson, Lynda Kaye; Killian, Christopher Moore; McCord, Elizabeth Forrester; McLain, Stephan James; Kreutzer, Kristina Ann; Ittel, Steven Dale; Tempel, Daniel Joseph
PA E. I. Du Pont De Nemours and Company, USA
SO U.S., 122 pp., Cont.-in-part of U.S. Ser. No. 473,590, abandoned.
CODEN: USXXAM
DT Patent
LA English
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5880241	A	19990309	US 1996-590650	19960124
	US 5866663	A	19990202	US 1997-891332	19970710
	US 5880323	A	19990309	US 1997-891331	19970710
	US 5886224	A	19990323	US 1997-891403	19970710
	US 5891963	A	19990406	US 1997-891442	19970710
	US 5916989	A	19990629	US 1997-891472	19970710
	US 6034259	A	20000307	US 1997-891398	19970710
	US 6107422	A	20000822	US 1997-899003	19970710
	US 6140439	A	20001031	US 1997-891405	19970710
	US 6218493	B1	20010417	US 1997-891224	19970710
PRAI	US 1995-378044	B2	19950124		
	US 1995-415283	B2	19950403		
	US 1995-473590	B2	19950607		
	US 1995-2654	P	19950822		
	US 1995-7375	P	19951115		
	US 1996-590650	A3	19960124		

AB Disclosed herein are processes for polymg. ethylene, acyclic olefins, and/or selected cyclic olefins, and optionally selected olefinic esters or

carboxylic acids, and other monomers. The polymns. are catalyzed by selected transition metal compds., and sometimes other cocatalysts.

Since some of the polymns. exhibit some characteristics of living polymns., block copolymers can be readily made. The polyolefins contain 80-150 branches/1000 CH₂ groups and 30-90 Et, 4-20 Pr, 15-50 Bu, 3-15 amyl, and 30-140 hexyl or longer branches per 100 Me branches. Numerous novel catalysts are disclosed, as well as some novel processes for making them. The polymers made are useful as elastomers, molding resins, in adhesives, etc. Also described herein is the synthesis of linear .alpha.-olefins by the oligomerization of ethylene using as a catalyst system a combination

a nickel compd. having a selected .alpha.-diimine ligand and a selected Lewis or Bronsted acid, or by contacting selected .alpha.-diimine nickel complexes with ethylene. A typical catalyst was manufd. by stirring 10 mL MeOH contg. 1 mL HCO₂H, 5 mmol 2-tert-butylaniline, and 15.4 mmol 2,3-butanedione overnight, and stirring

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10 mL MeCN contg. 0.395 mmol resulting intermediate 5 min with
(1,5-cyclooctadienyl) (methyl)acetonitrilepalladium hexafluoroantimonate.
RE.CNT 42
RE
(1) Anderson; US 3265622 1966 CAPLUS
(2) Anon; GB 1034197 1966 CAPLUS
(4) Anon; FR 2355854 1977 CAPLUS
(5) Anon; GB 2058094 1980 CAPLUS
(6) Anon; EP 0193202 A2 1986 CAPLUS
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L8 ANSWER 5 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1997:765323 CAPLUS
DN 128:108480
TI Photopolymerizable compositions with high laser sensitivity and
lithographic plates using the same
IN Matsumoto, Shinji; Kuroki, Takaaki; Hattori, Yoshiji; Maehashi, Tatsuichi
PA Konica Co., Japan
SO Jpn. Kokai Tokkyo Koho, 15 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1
PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 09309907 A2 19971202 JP 1996-125657 19960521
AB Title compns., showing high sensitivity with laser exposure, include (A)
ethylenically-unsatd. monomers, (B) Lewis acids MXn (M = B, Al, Fe, Sn,
Zn; X = halo; n = 1-3), and (C) onium salts, halo-contg. triazine
compds.,
Fe-arene complexes, and/or bisimidazoles. The A and B may be
microcapsuled. Title lithog. plates have layers of above compns. on
hydrophilic supports.

L8 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1996:554708 CAPLUS
DN 125:171363
TI Decorative boards for pachinko pinball machines
IN Shioda, Yozo; Nakagawa, Hiroshi
PA Sumitomo Bakelite Co, Japan
SO Jpn. Kokai Tokkyo Koho, 4 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1
PATENT NO. KIND DATE APPLICATION NO. DATE

PI JP 08156214 A2 19960618 JP 1994-295386 19941129
AB Decorative paper is impregnated with aq. melamine resin varnishes contg.
water-sol. blocked isocyanates and Lewis acid-Mg
complexes to prep. decorative boards. Thus, decorative paper was
impregnated with a varnish contg. a melamine resin 100, powd. cellulose
2,
silica 4, a Me Et ketoxime-blocked isocyanate 1.5, and a Lewis
acid-Mg complex 0.2 part to prep. a decorative sheet and
pressed on a phenolic resin core to prep. a pachinko board.

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L8 ANSWER 7 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1995:677388 CAPLUS
DN 123:55587
TI Method of preparing 2,7-[2-(2-aminothiazol-4-yl)-2-
(methoxyiminoacetylamino)]-3'- (2-methyl-5,6-dioxo-1,2,5,6-tetrahydro-1,2,4-
triazin-3-ylthio)deacetoxycephalosporanic acid [ceftriaxone]
IN Winiarski, Jerzy; Grochowski, Edward; Prosciewicz, Boguslaw; Pankowski,
Jacek; Boleslawska, Teresa; Cieslak, Marek; Gwiazda, Piotr; Szymanski,
Jerzy; Nowakowska, Krystyna; Et, Al.
PA Polska Akademia Nauk, Instytut Chemii Organicznej, Pol.
SO Pol., 4 pp.
CODEN: POXXA7
DT Patent
LA Polish
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI PL 163399	B1	19940331	PL 1990-287590	19901031

OS CASREACT 123:55587
GI For diagram(s), see printed CA Issue.
AB The 3rd-generation antibiotic ceftriaxone (I) and/or its tautomers are
prepd. by reaction of cephalosporanic acid deriv. II with
triazinethiol deriv. III and/or its tautomers, in an org. solvent and in
the presence of a Lewis acid catalyst at -10.degree.
to +40.degree., followed by known isolation methods (esp. aq. diln., pH
adjustment, and filtration). Suitable Lewis acids include
halides of Zn, Sn, Ti, B, or Al, free or as complexes with electron
donors
such as ethers, amines, or amides. For example, 20 mL BF₃.OEt₂ was added
dropwise to a suspension of 10 g II and 5 g III in 40 mL MeCN, and the
mixt. was stirred at 0.degree. for 60 min, poured into ice-water, and
neutralized to pH 7 with aq. NH₃. Decolorization with active C,
acidification to pH 2.7-3.0 with 1:1 HCl, filtration, etc., gave I. Ten
addnl. example runs are described, with yields of 10-66%, the latter case
using BF₃.OEt₂ in EtOAc in the presence of DMF at 20.degree..

L8 ANSWER 8 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1989:523842 CAPLUS
DN 111:123842
TI Photoresist for forming pattern with reticulation-resistant surface layer
IN Fisher, Thomas A.
PA Shipley Co., Inc., USA
SO Eur. Pat. Appl., 9 pp.
CODEN: EPXXDW
DT Patent
LA English
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI EP 309682	A2	19890405	EP 1988-112223	19880728
EP 309682	A3	19901227		
	R: DE, FR, GB, IT			
US 4873176	A	19891010	US 1987-90753	19870828
JP 01128062	A2	19890519	JP 1988-214756	19880829

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US 5538820	A	19960723	US 1993-108777	19930818
PRAI US 1987-90753		19870828		
US 1988-288221		19881222		
US 1990-617967		19901121		

AB A method for forming a photoresist mask on a substrate (i.e. integrate circuit substrate) resistant to reticulation during plasma etching comprises the steps of forming an imaged and developed pos.-working photoresist layer comprising a novolak resin, an o-quinonediazidesulfonic acid ester, and an unreacted acid-activated crosslinking agent and subjecting the substrate to an etching plasma in a gaseous stream contg. a **Lewis acid**. Contact of the surface of the developed photoresist film with the **Lewis acid** causes crosslinking of the surface of the developed photoresist film during plasma etching with the formation of a reticulation-resistant surface layer. Thus, a photoresist compn. comprised of a novolak resin,

a 1-oxo-2-diazonaphthoquinone-5-arylsulfonate, a dye, a leveling agent, an adhesion **promoter**, and hexamethoxymethylmelamine was coated on an Al substrate, baked, imagewise exposed to a Hg lamp. developed, and plasma etched using a gas mixt. of Cl₂, CHCl₃, and BF₃ with H₂ as the carrier gas to give a wafer having a surface free of reticulation.

L8 ANSWER 9 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1989:192953 CAPLUS
DN 110:192953
TI Halocyclogermazanes. Effect of the halo substituent on the existence of a cyclogermazane-germaimine equilibrium
AU Riviere-Baudet, M.; Khallaayoun, A.; Satge, J.
CS Lab. Chim. Organomineraux, Univ. Paul Sabatier, Toulouse, 31602, Fr.
SO Recl. Trav. Chim. Pays-Bas (1988), 107(3), 152-9
CODEN: RTCPA3; ISSN: 0165-0513
DT Journal
LA French
OS CASREACT 110:192953
AB Studies of ring opening of chlorocyclotrigermazanes in cycloaddn. reactions with the nitrones phenyl- and tert-butylbenzylideneamine N-oxide, catalyzed by Lewis bases (HMPA) or Lewis acids (ZnCl₂, M(CO)₆, M(CO)₅.cntdot.THF, M = Cr, W), show that hexachlorocyclotrigermazanes are much less reactive than the corresponding methylcyclogermazane. The decreased reactivity is attributed to the tendency of the electron-attracting chlorine atoms to promote the back-donation of electrons from nitrogen to germanium, thereby rendering the Ge-N bond less polar and therefore less susceptible to coordination (either with Lewis acids or Lewis bases) and attack by polar reagents such as carbonyl compds.

L8 ANSWER 10 OF 12 CAPLUS COPYRIGHT 2001 ACS
AN 1987:599926 CAPLUS
DN 107:199926
TI Adhesives for metal-plated laminates
IN Maeda, Masanori; Otsuka, Nobuyuki
PA Matsushita Electric Works, Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 2 pp.
CODEN: JKXXAF
DT Patent

V. Balasubramanian

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 62132986	A2	19870616	JP 1985-274081	19851204
AB	The title adhesives, with good storage stability, comprise epoxy resins, melamine resins, poly(vinyl butyral) (I), isocyanates, Lewis acid catalysts, and org. solvents contg. cyclohexanone (II). Thus, 2 parts Epikote 153 was mixed with melamine resin 7, I 10, isocyanate 1, BF3-400 (BF3-monoethylamine complex) 0.02, II 15, MEK 40, and MeOH 24.98 parts to give an adhesive, which showed gel time just after prepn. 215 s, after 30 days storage at 40.degree. 215 s. A phenolic resin-impregnated laminate was bonded with Cu foil with the adhesive to give a sample showing soft solder heat resistance just after prepn. 30 s, after 30 days storage at 40.degree. 30 s, vs. 30 s, 9 s, resp. without II, which showed gel time just after prepn. 210 s, after 30 days storage at 40.degree. 540 s.				

L8 ANSWER 11 OF 12 CAPLUS COPYRIGHT 2001 ACS

AN 1985:78246 CAPLUS

DN 102:78246

TI Chemometrics of basicity. 1. Comparison of the basicity of o-, m-, and p-substituted pyridines toward boron trifluoride and methanol

AU Berthelot, Michel; Gal, Jean Francois; Laurence, Christian; Maria, Pierre Charles

CS Lab. Spectrochim. Mol., Univ. Nantes, Nantes, 44072, Fr.

SO J. Chim. Phys. Phys.-Chim. Biol. (1984), 81(5), 327-31

CODEN: JCPBAN; ISSN: 0021-7689

DT Journal

LA French

AB For BF3 or MeOH complexes with pyridines, the enthalpy of **complex** formation with BF3 is linearly correlated to the shift of the hydroxyl stretching vibration of MeOH. This correlation is obeyed by all meta substituents but only by -R para substituents. The + R para-substituted pyridines appear relatively more basic towards BF3, whereas ortho-substituted pyridines appear relatively more basic towards MeOH. Therefore the variable resonance effects of + R substituents and the steric effects of ortho-substituents prevent the definition of a general basicity scale. The range of validity of DN, B, or β . scales should be restricted as soon as the basicity-dependent property is obtained from a **Lewis acid** differing in strength or steric requirement from those used in the definitions.

L8 ANSWER 12 OF 12 CAPLUS COPYRIGHT 2001 ACS

AN 1978:482980 CAPLUS

DN 89:82980

TI Polymerized vinyl carbazoles sensitized by nitro-substituted 9-dicyanomethylene fluorenes

IN Hoegl, Helmut; Barchietto, Giacomo

PA Xerox Corp., USA

SO U.S., 12 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

PATENT NO.

KIND DATE

APPLICATION NO. DATE

V. Balasubramanian

PI US 4069046 A 19780117 US 1974-437573 19740129
PRAI US 1967-652278 19670710
US 1971-116989 19710219
AB A photoconductive insulating coating material for electrophotog. plates
is comprised of a charge-transfer **complex** prep'd. from an arom.
resin and a nitro-substituted 9-dicyanomethylenefluorene. The arom.
resin is selected from poly(N-vinylcarbazole), styrene resins, phenol-aldehyde
resins, polycarbonates, epoxy resins, phenoxy resins, and polyurethanes.
Thus, a polyphenylene oxide resin (PPO-531, General Elec. Co.) 4 parts
was dissolved in C6H4Cl2 50 parts. To this soln. was added a soln. comprised
of 9-dicyanomethylene-2,4,5,7-tetranitrofluorene 1, cyclohexanone 10, and
C6H4Cl2 20 parts. The resulting soln. was then coated to a 7-.mu.
thickness on a 5-mil Al plate by flow coating, dried, and used at
100.degree. for 30 min. The plate was charged to -600 V by means of a
corona discharge, exposed by projection at 180 ft-candle-s, and cascade
developed. The developed image was then electrostatically transferred to
a receiving sheet and fused thereon.

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